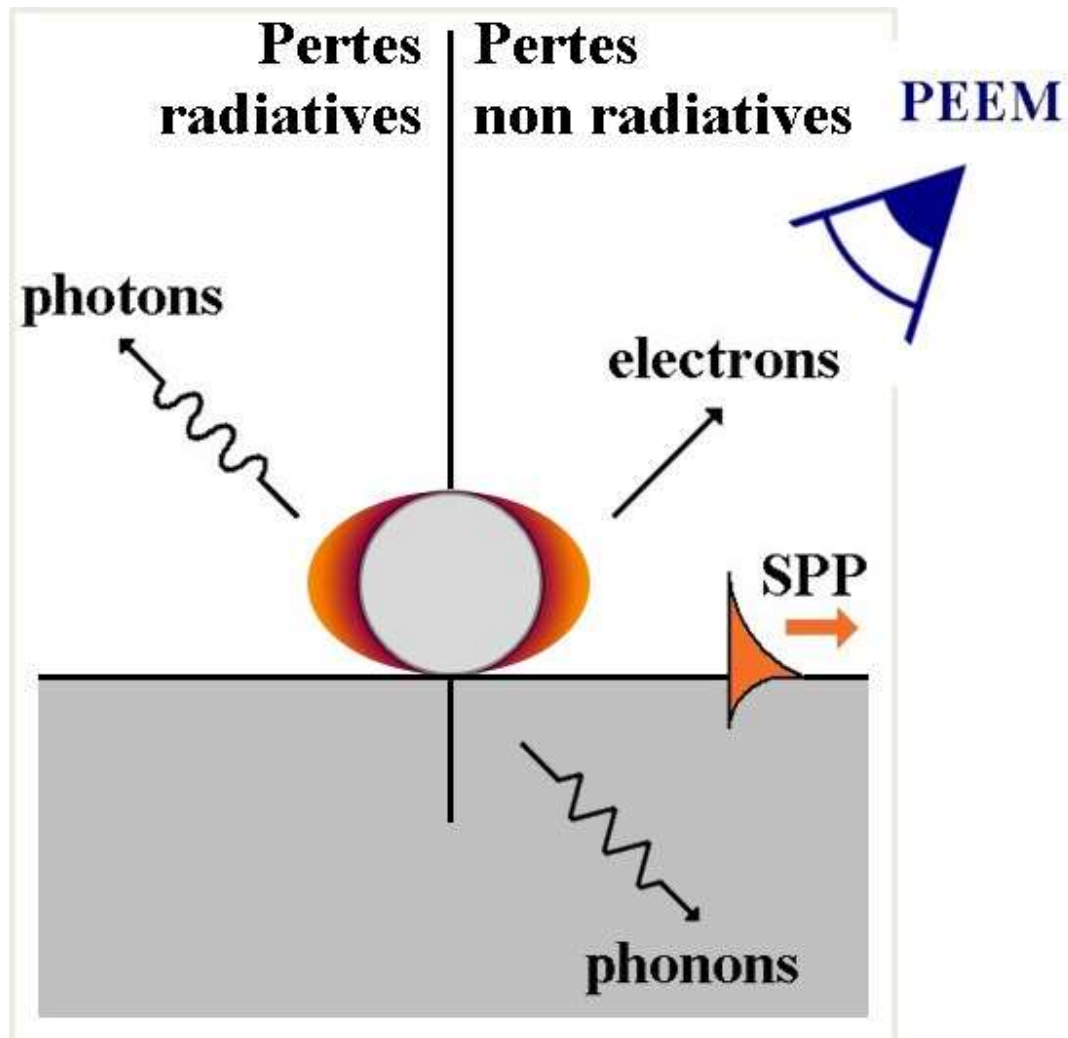


Coupler photons & électrons. La microscopie électronique, un outil pour l'optique champ proche

Coupling photons & electrons. Electron microscopy, a tool for near field optics



L. Douillard

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iramis.cea.fr/spec/

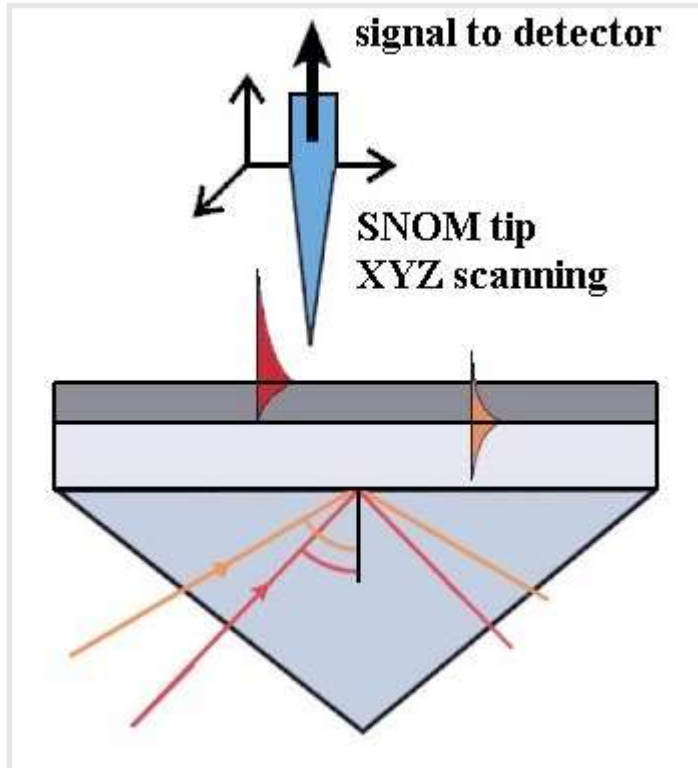
CEA IRAMIS SPEC

UMR CNRS 3680

Université Paris-Saclay

Mapping the evanescent field at the nanometre

SNOM/NSOM - *scanning near-field optical microscopy* (1984...)



➤ Basic principle

.scanning probe microscopy SPM. Closely related to scanning tunnelling microscopy STM

.introduction of a tip (glass fiber, metal...) in the near field of the object to be studied – **intrusive technique**

.routine resolution 50 - 100 nm

.many variants (illumination and collection modes)

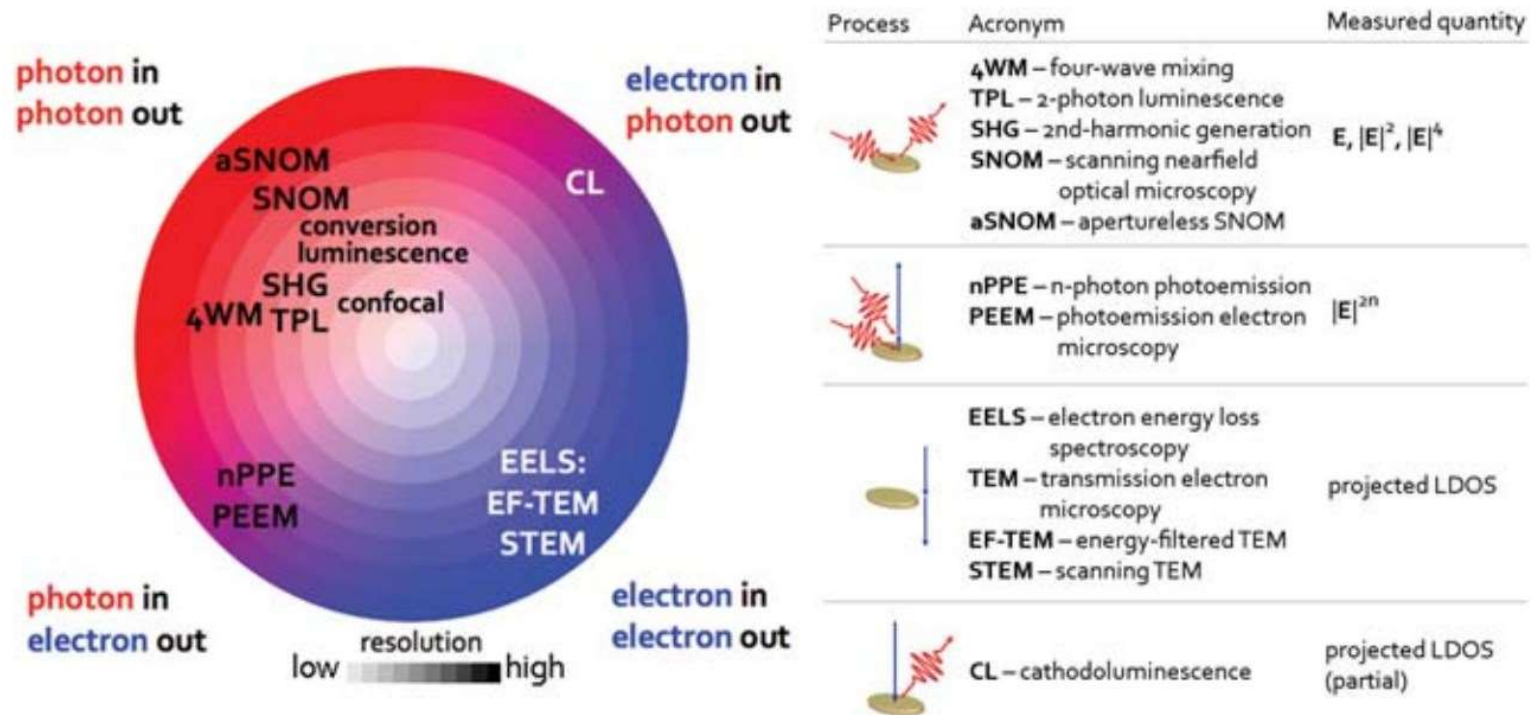
➤ Drawbacks

.low reproducibility of tips

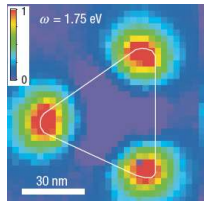
.possible perturbation of the evanescent field due to LSP excitation and lightning-rod geometric effect at the tip-surface junction

Mapping the evanescent field at the nanometre

Alternative non intrusive methods

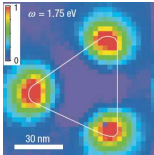


- STEM EELS *scanning transmission microscopy in electron energy loss spectro. mode* (electron in, electron out) = Mapping of an electron energy loss signature
- CL *cathodoluminescence* (electron in, photon out) related to EELS
- PEEM *photoemission electron microscopy* (photon in, electron out), other acronym = n-PPE *n photon photoemission*



Electron Energy Loss Spectrometry EELS

A tool for near field optics



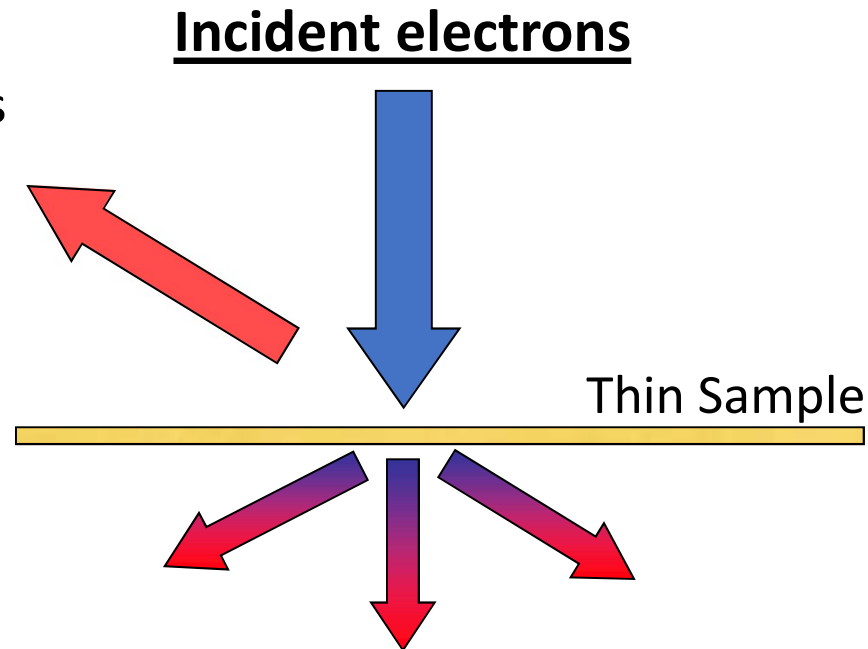
Electron energy loss spectrometry, a tool for near field optics

Basic principle – Electron energy loss mapping

➤ To probe locally a sample (surface, thin film, particle) with a focused electron beam and investigate its excitations using the inelastically diffracted / scattered electrons

Secondary electrons
Backscattered electrons
Auger electrons

SEM, AES



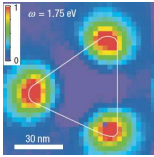
Inelastically diffracted and scattered electrons
♦ Individual excitations
♦ Collective excitations

EELS Spectrometry

Transmitted electrons
TEM Bright Field Imaging

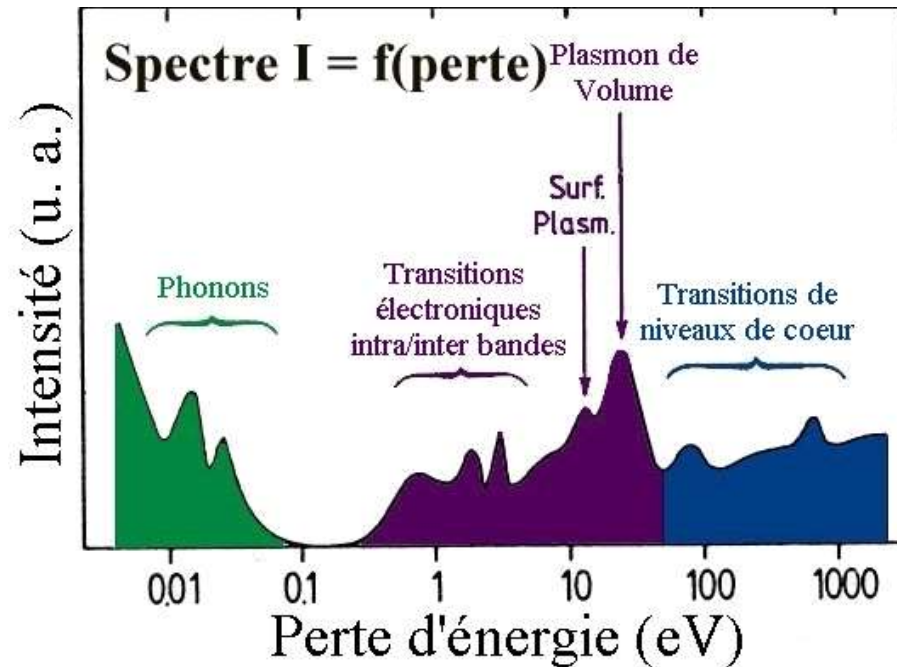
Elastically scattered and diffracted electrons

**HR Diffraction (HA)ADF
Holography**



Electron energy loss spectrometry, a tool for near field optics

Basic principle – Electron energy loss spectrum



Zero loss region – Low primary energies, high energetic resolution

$$1 \text{ meV} < \Delta E < 100 \text{ meV}$$

→ High Resolution Electron Energy Loss Spectrometry HREELS

Low loss region

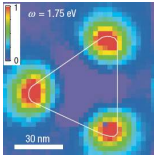
$$100 \text{ meV} < \Delta E < 50 \text{ eV}$$

→ Electron Energy Loss Spectrometry EELS

High loss region – High primary energies

$$\Delta E > 50 \text{ eV}$$

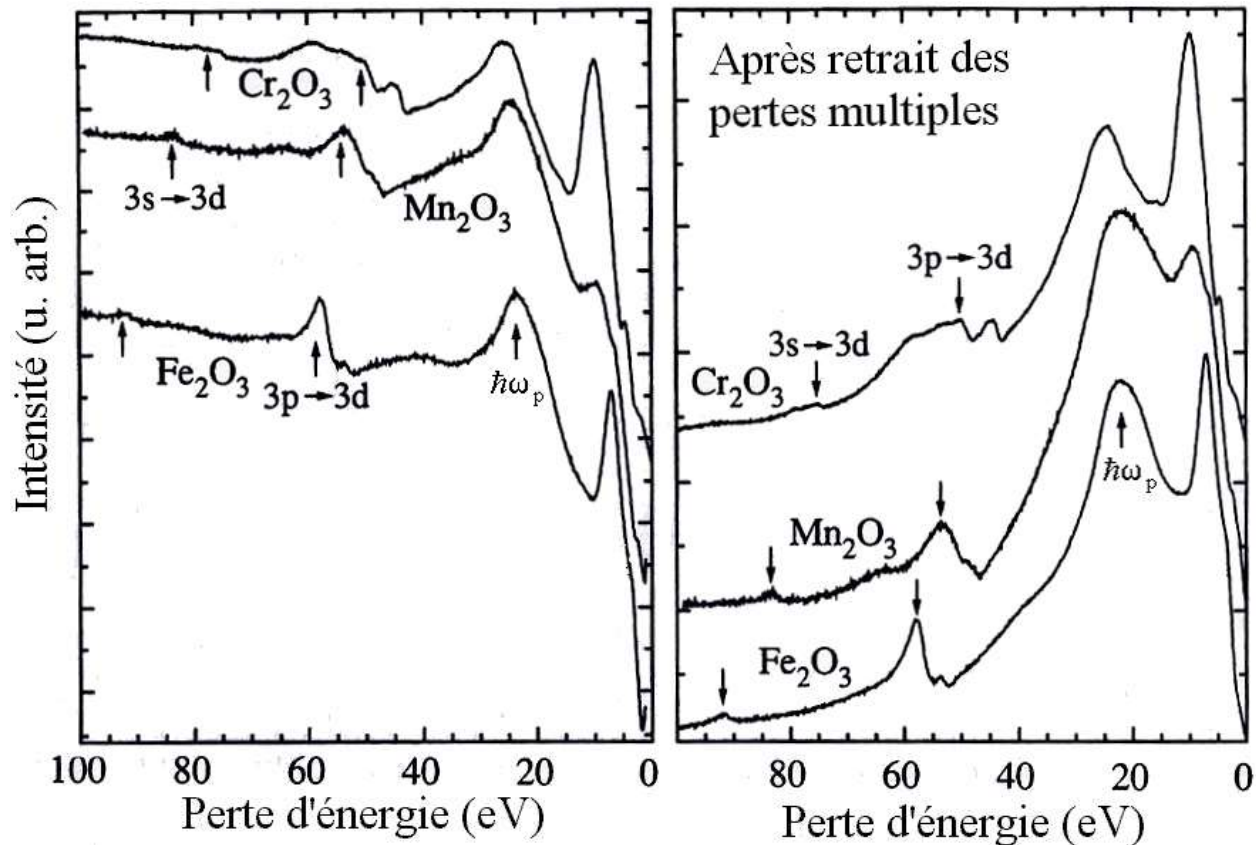
→ EXtended Electron energy Loss Fine Structures EXELFS



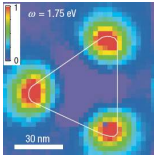
Electron energy loss spectrometry, a tool for near field optics

Basic principle – EELS, loss region $100 \text{ meV} < \Delta E < 50 \text{ eV}$

- Excitation mechanism n°1
 - Individual excitations
 - Electronic intra-, resp. interband transitions



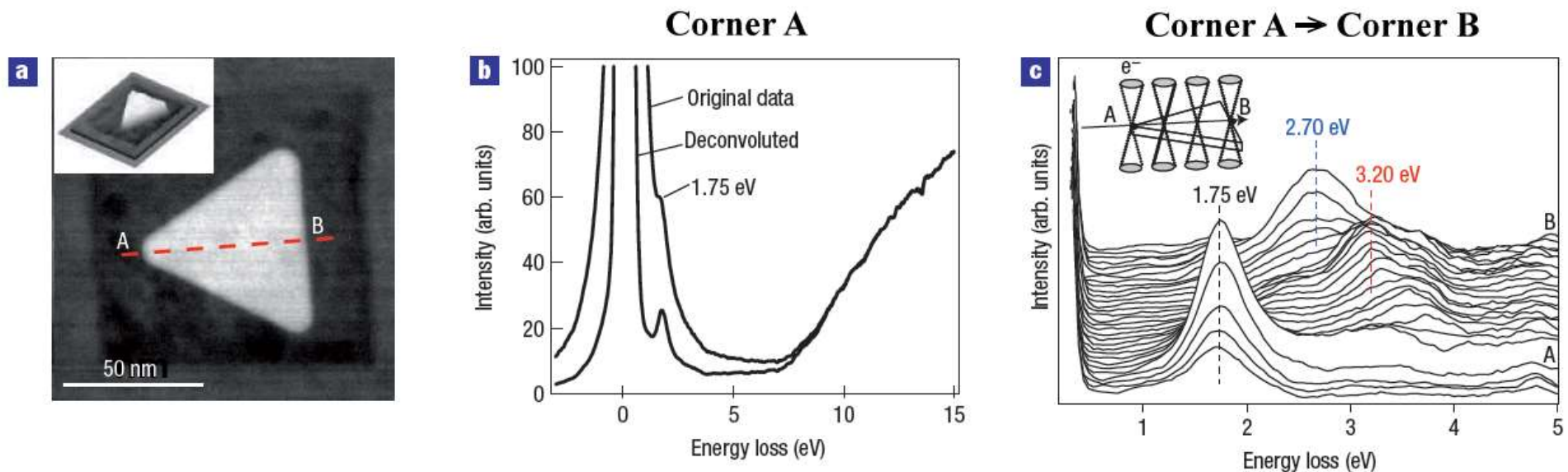
Electron energy loss spectra of transition metal oxides R. Zimmerman PhD (1996)



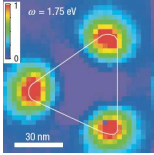
Electron energy loss spectrometry, a tool for near field optics

Basic principle – EELS, loss region $100 \text{ meV} < \Delta E < 50 \text{ eV}$

- Excitation mechanism n°2
- Collective excitations
- Surface and bulk plasmons**



- (a) Regular Au nanoprism particle. HAADF-STEM imaging
- (b) EELS spectra acquired at corner A. One plasmon loss peaks at 1.75 eV
- (c) A series of 32 successive low loss STEM EELS spectra acquired along the line A - B of the nanoprism. Three plasmon resonances are detected 1.75, 2.70 and 3.20 eV



Electron energy loss spectrometry, a tool for near field optics

Basic principle – EELS probability Γ_{EELS} for a small sphere $a \ll \lambda$

- The transient electric field associated to the e-beam is similar to a plane wave pulse of white light (at 100 keV, $v_e = 164$ nm/fs). The nanoparticle (NP) sees a pulse containing a large spectrum of frequencies. (e, e) Coulombian coupling in nature,
- All the energy absorbed or scattered by a plasmonic particle has to be provided by the incident electrons. So, full electron losses are proportional to the particle extinction cross section

$$\Gamma_{\text{EELS}}^{\text{sphere}}(R_{\perp}, \omega) = \frac{4e^2 a}{\pi \hbar v^2} \sum_{l=1}^{\infty} \sum_{m=-l}^l \frac{(a\omega/v)^{2l} (2 - \delta_{0,m})}{(l+m)!(l-m)!} K_m^2 \left(\frac{\omega R_{\perp}}{v} \right) \Im \{ \alpha_l(\omega) \}$$

a Sphere diameter

$R_{\perp} = (x, y)$ Impact parameter of the electrons traveling along the z direction at speed v ,

$\hbar\omega$ Loss energy, ω pulsation = $2\pi \cdot$ frequency

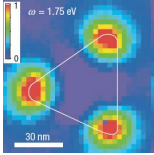
K_m Modified Bessel function of the second kind

\Im Imaginary part

α_l Sphere polarizability for mode l

Non relativistic electrons. For relativistic electrons the Lorentz factor $\gamma = 1/\sqrt{1 - v^2/c^2}$ has to be considered

- **EELS depends on all resonance modes l of the NP**



Electron energy loss spectrometry, a tool for near field optics

Basic principle – EELS probability Γ_{EELS} for a small sphere $a \ll \lambda$

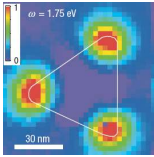
- The e-beam electric field is similar to a plane wave pulse of white light. The NP sees a pulse containing a large spectrum of frequencies
- In the quasi-static QS approximation, the exciting field is static, *i.e.*, presents no spatial variation over the particle. Thus, it couples only to the $l=1$ dipolar mode

$$\Gamma_{EELS}^{sphere}(\omega, R_{\perp}) \propto \left(\frac{\omega}{\gamma v^2}\right)^2 \Im(\alpha_{l=1}(\omega)) \left(K_1^2\left(\frac{\omega R_{\perp}}{\gamma v}\right) + \frac{1}{\gamma^2} K_0^2\left(\frac{\omega R_{\perp}}{\gamma v}\right) \right)$$

$$\Gamma_{EELS}^{sphere}(\omega, R_{\perp}) \propto \Im(\alpha_{l=1}(\omega)) \cdot \exp\left(-\frac{R_{\perp}}{\gamma v/\omega}\right)$$

$$\sigma_{ext.} \cong \sigma_{abs.} \propto \Im(\alpha_{l=1}(\omega))$$

- EELS probability of a small sphere is proportional to its extinction (absorption) cross-section as measured in far field optics, $\sigma_{ext.} \cong \sigma_{abs.} \propto \Im(\alpha_{l=1}(\omega)) \propto a^3$
- EELS probability is position-dependent with a quasi-exponential decay with e-beam to sphere distance R_{\perp} , attenuation length = $\gamma v/\omega \sim 10 - 100$ nm



Electron energy loss spectrometry, a tool for near field optics

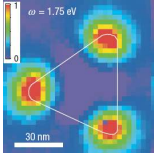
Basic principle – EELS probability Γ_{EELS} vs EMLDOS

In quasi-static approximation

$$\Gamma_{EELS}^{sphere}(\omega, \vec{R}_{\perp}) = \frac{e^2}{\pi \hbar \omega^2} \sum_i \Im(f_i(\omega)) \left| TF_z(\vec{E}_i^z(\vec{R}_{\perp}, \frac{\omega}{v})) \right|^2$$

f_i generalized polarizability, *i.e.*, the spectral dependence of the plasmon (plasmon energies = f_i poles); TF_z is a Fourier transform along the e-beam direction at point $\vec{R}_{\perp} = (x, y)$ in real space and momentum $q_z = \omega / v$ in reciprocal space of the electron induced nearfield electric field.

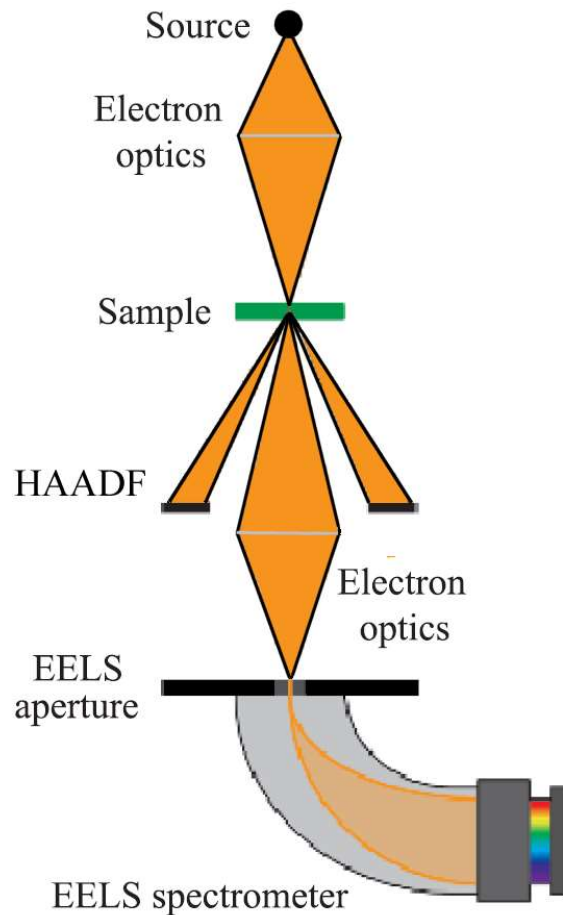
- Within a TF_z , EELS maps spectrally and spatially the zEMLDOS, *i.e.*, the electromagnetic density of states in the direction along the e-beam axis
- EELS = Out-of-plane EMLDOS ($\vec{v}_e \cdot \vec{E}_{ind} = \vec{v}_{e,z} \cdot \vec{E}_{ind,z}$)
- Electron selection rules \neq photon selection rules \rightarrow Dark modes accessible
- Not a true optical process, so no direct control over the near field polarization



Electron energy loss spectrometry, a tool for near field optics

Instrumentation – STEM EELS mode

STEM - EELS



➤ Scanning transmission electron microscope in electron energy loss mode - (electron in, electron out) process

Electron source (electron field gun)

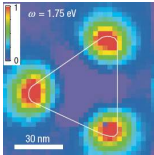
Electron optics

Energy = Hundreds of keV (TEM)

The electron beam is focused and raster scanned on the sample. Beam diameter $\varnothing \leq 1$ nm

EELS spectrometer for the extraction of the EELS spectrum at precise (x, y) position – Serial recording

➤ **Near field imaging through the mapping of a particular electron energy loss (plasmon energy). Spatial resolution \approx beam diameter**

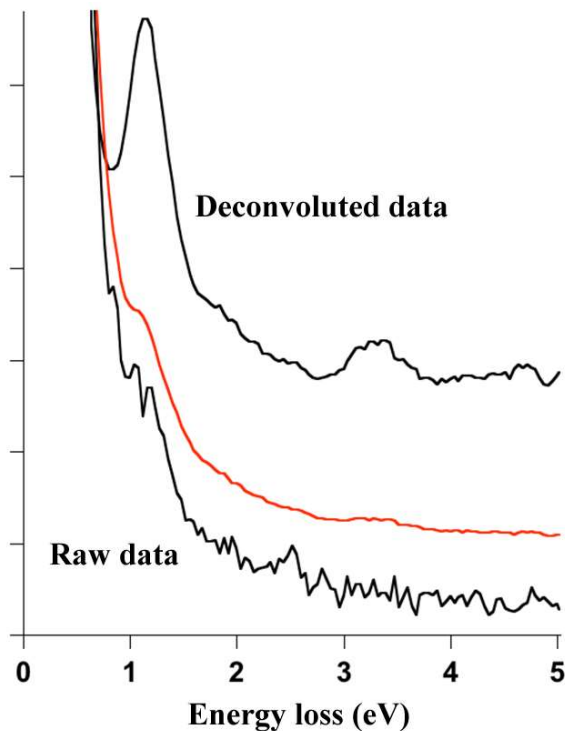


Electron energy loss spectrometry, a tool for near field optics

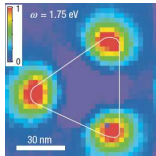
Instrumentation – STEM EELS Difficulties & Limitations

➤ How to get rid of the Zero Loss Peak ZLP

- ◆ The major experimental issue is to get at the same time both high energy- ($\delta E = 100$ meV) and high spatial- ($\delta R = 0.1$ nm) resolutions
- ◆ Thank to high brightness electron gun developments, beam monochromation (δE) is possible without too large drops of brightness (δR)
- ◆ Numerical treatments for better spectral deconvolution are now available. PSF deconvolution, Richardson-Lucy Deconvolution Gloter *et al.* Ultramicroscopy **96** (2003) 385
- ◆ Less noisy and faster CCD detectors are available

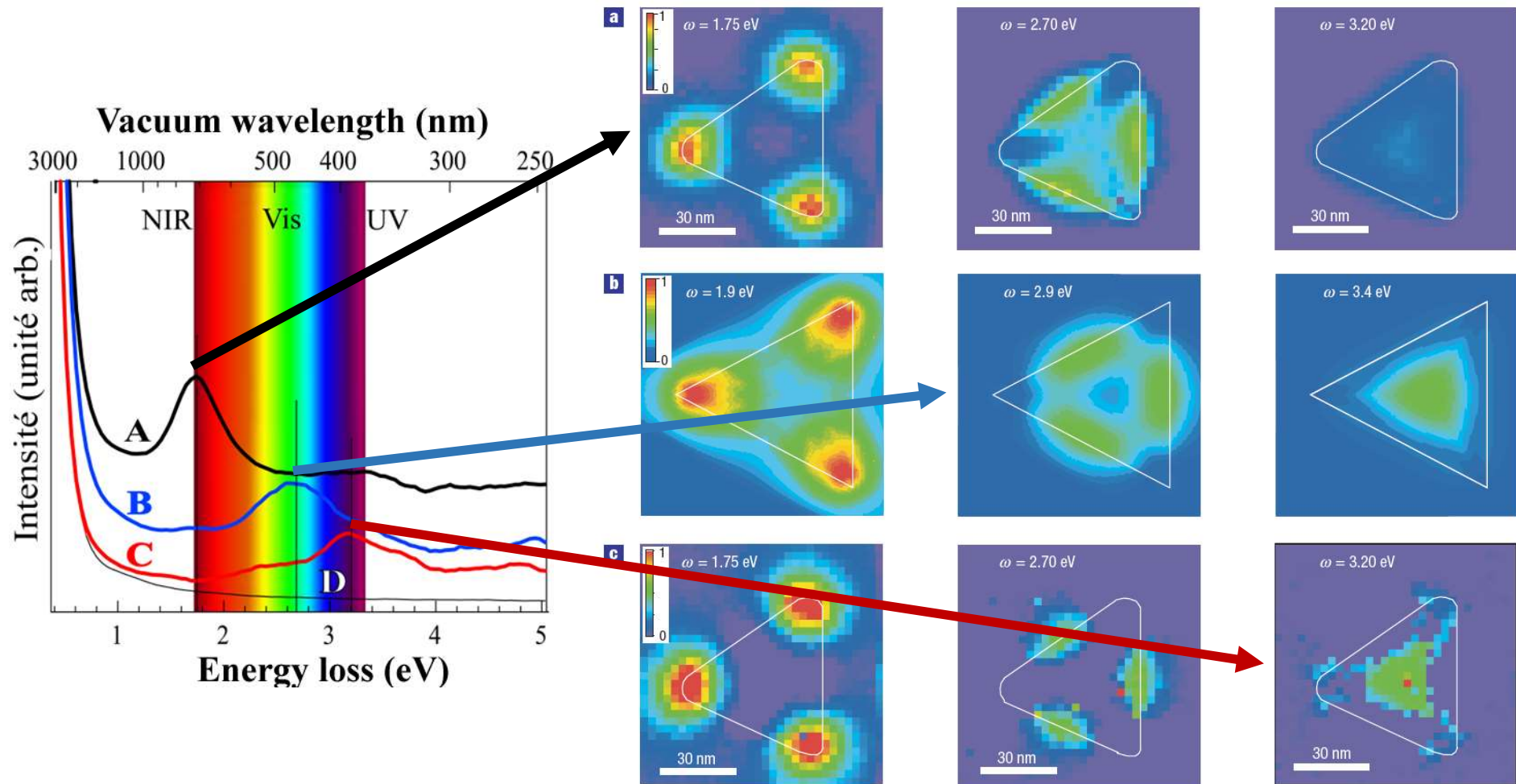


➤ Electron monochromator resolution is now down to 10 meV = 0.01 eV (2019)

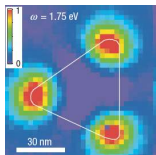


Plasmonics of 2D objects - NanoPrism D_{3h} - STEM EELS

EELS near field imaging

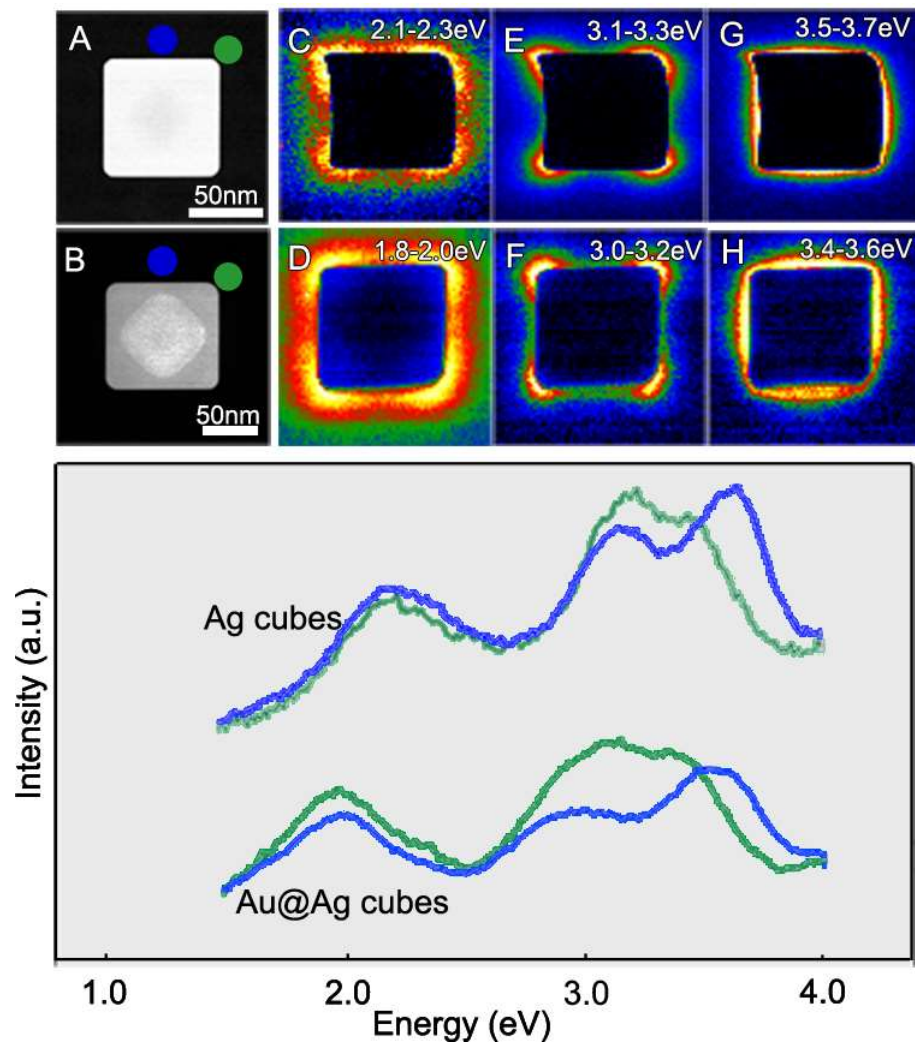


Regular nanoprism 78 nm. Near field Imaging. Resonance modes, $m = \{1, 2, 3\}$ – STEM EELS
 (a) Raw exp data – ZLP, (b) FDTD simulation , (c) Gaussian fitting of the exp. data



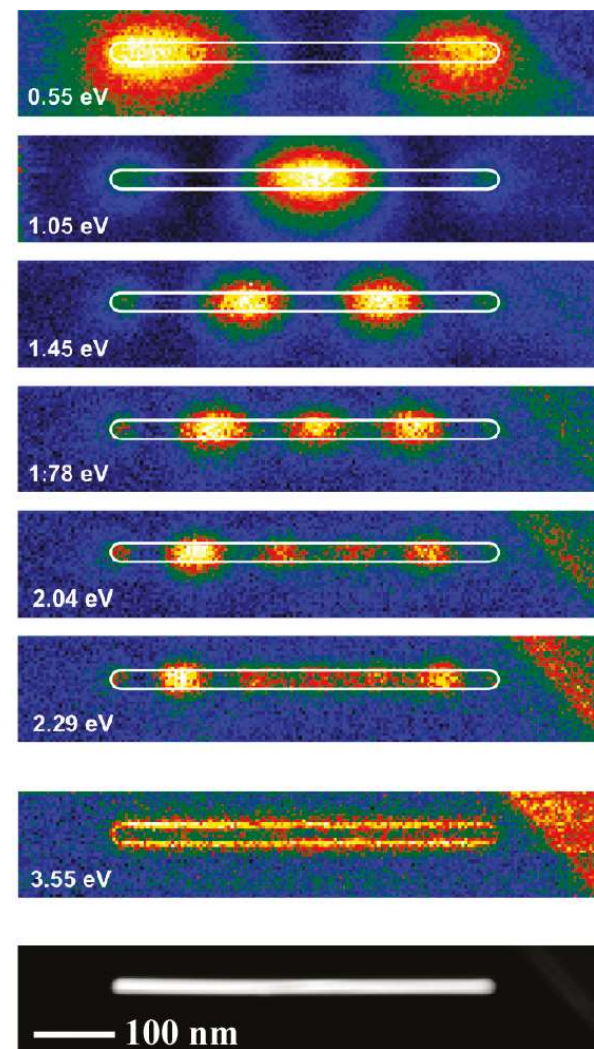
Plasmonics of Nanoobjects – Cubes & Rods - STEM EELS

EELS near field imaging



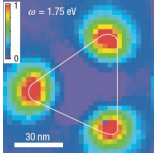
Ag and Au@Ag NanoCubes 70 nm

B. Goris *et al.* *J. Phys. Chem. C* **118** (2014) 15356



Ag NanoRods, 14 nm in diameter

D. Rossouw *et al.* *Nano Lett.* **11** (2011) 1499



Electron energy loss spectrometry, a tool for near field optics

EELS near field imaging - Variants & Advances

- ◆ EELS 3D tomography

- 3D mapping of plasmon resonances O. Nicoletti *et al. Nature* **502** (2013) 80; A. Hörl *et al. Phys. Rev. Lett.* **111** (2013) 076801

- ◆ Time-resolved EELS measurements in the fs time range

- Use of a pulsed optical excitation combined with a pulsed electron probe
F. Carbone *et al. Science* **325** (2009) 181

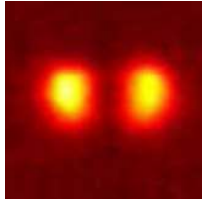
- ◆ Vortex EELS measurements

- Use of an electron beam that carries an angular orbital momentum (diffractive phase plate, magnetic lens aberrations)

Applications = Measurement of magnetic phenomena at the nanoscale

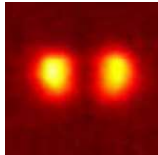
Magnetic plasmon mapping Z. Mohammadi *et al. Opt. Express* **20** (2012) 15024

Magnetic dichroism measurements in plasmonic structures X. Zambrana-Puyalto *et al. Nat. Commun.* **5** (2014) 4922



Cathodoluminescence CL

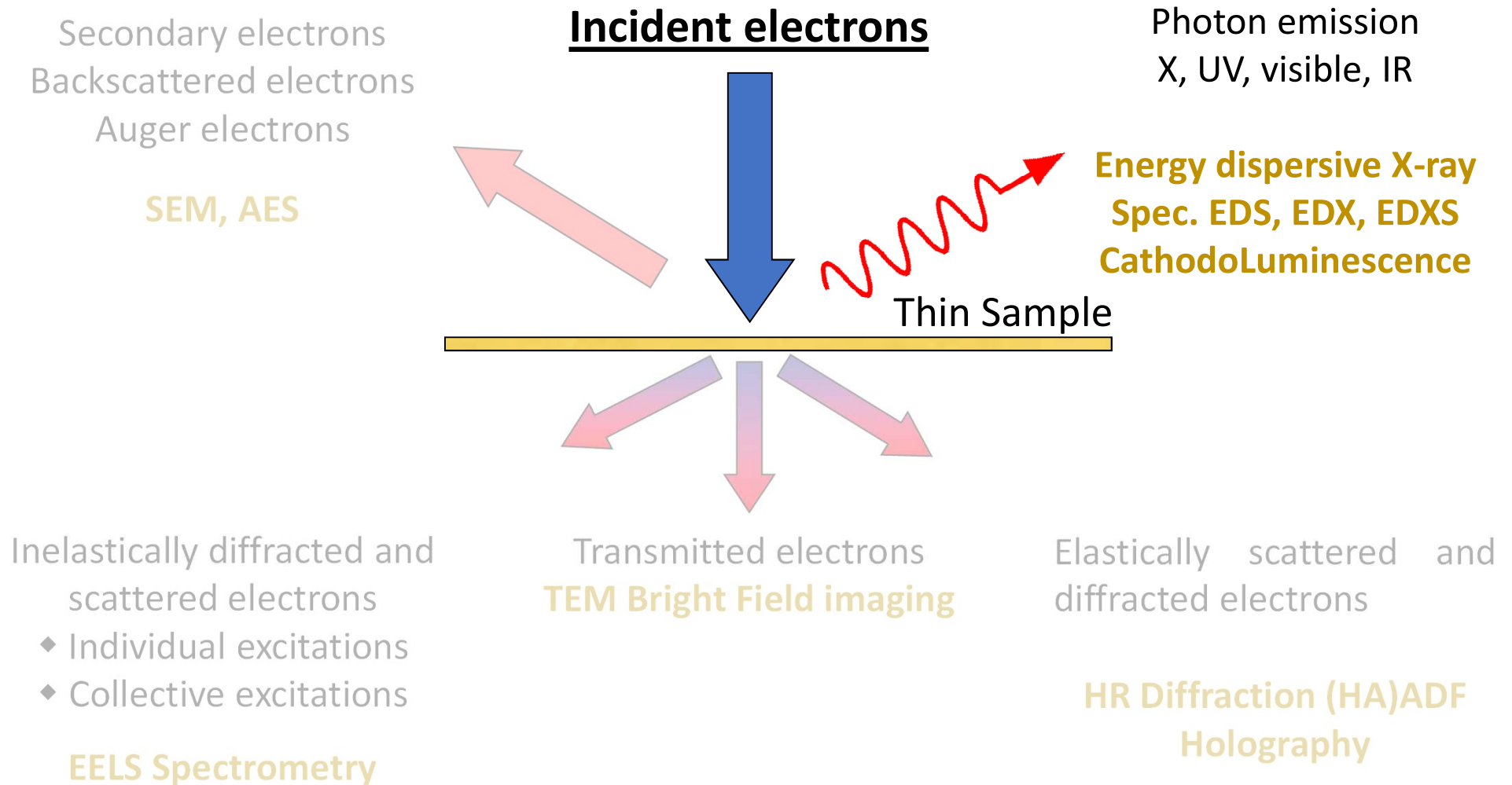
A tool for near field optics

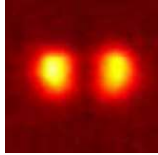


Cathodoluminescence, a tool for near field optics

Basic principle – Cathodoluminescence near field imaging

- To probe locally a sample (surface, thin film, object) with a focused electron beam and investigate its excitations by collecting the emitted light (vis. spectrum)





Cathodoluminescence, a tool for near field optics

Basic principle – Coherent CL probability Γ_{CL} of a small sphere

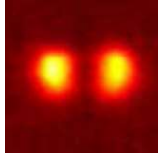
- The transient electric field associated to the e-beam is similar to a plane wave pulse of white light. The NP sees an EM pulse containing a large spectrum of frequencies
- In the QS approximation, the exciting field is static, *i.e.*, presents no spatial variation over the particle size. Thus, it couples only to the $l=1$ dipolar mode

$$\Gamma_{CL}^{sphere}(\omega, R_{\perp}) \propto \omega^3 \left(\frac{\omega}{\gamma v^2}\right)^2 |\alpha_{l=1}(\omega)|^2 \left(K_1^2\left(\frac{\omega R_{\perp}}{\gamma v}\right) + \frac{1}{\gamma^2} K_0^2\left(\frac{\omega R_{\perp}}{\gamma v}\right) \right)$$

$$\Gamma_{CL}^{sphere}(\omega, R_{\perp}) \propto |\alpha_{l=1}(\omega)|^2 \exp\left(-\frac{R_{\perp}}{\gamma v/\omega}\right)$$

a Sphere diameter; $R_{\perp} = (x, y)$ Impact parameter of the electrons traveling along the z direction at speed v ; $\hbar\omega$ Energy of the emitted photon; K_m Modified Bessel function of the second kind; α_l Sphere polarizability for mode l

- CL probability of a small sphere Γ_{CL} is proportional to its scattering cross section as measured in far field optics, $\sigma_{sca.} \propto |\alpha_{l=1}(\omega)|^2 \propto a^6$
- CL probability is position-dependent with a quasi-exponential decay with e-beam to sphere distance R_{\perp} , attenuation length $\gamma v/\omega \sim 10 - 100$ nm
- Radiative bright field modes accessible



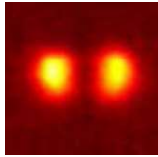
Cathodoluminescence, a tool for near field optics

Basic principle – Coherent CL probability Γ_{CL} of any particle

$$\begin{aligned}
 \Gamma_{CL}(\omega, \vec{R}_{\perp}) &= \frac{\omega e^2}{4\pi^2 \hbar c^3} \sum_i \sum_j f_i(\omega) f_j^*(\omega) \int_{\Omega_D} d\Omega \vec{p}_{i\perp}(\Omega) \cdot \vec{p}_{j\perp}^*(\Omega) \cdot TF_z(\vec{E}_i^z(\vec{R}_{\perp}, \frac{\omega}{v})) \cdot TF_z(\vec{E}_j^{z*}(\vec{R}_{\perp}, \frac{\omega}{v})) \\
 \Gamma_{CL}(\omega, \vec{R}_{\perp}) &= \frac{\omega e^2}{4\pi^2 \hbar c^3} \sum_i |f_i(\omega)|^2 \int_{\Omega_D} d\Omega |\vec{p}_{i\perp}(\Omega)|^2 \cdot \left| TF_z\left(\vec{E}_i^z\left(\vec{R}_{\perp}, \frac{\omega}{v}\right)\right) \right|^2 \\
 &+ \sum_i \sum_{j < i} \text{coupled intermode terms } (\vec{p}_{i\perp}, \vec{p}_{j\perp}^*)
 \end{aligned}$$

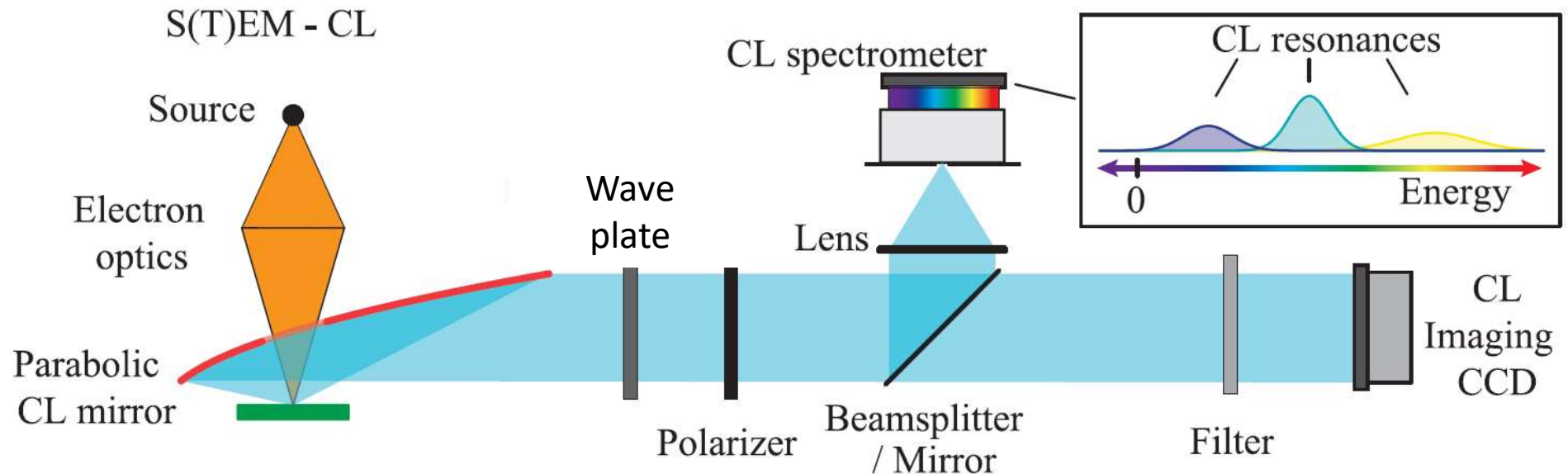
Where $f_i(\omega)$ is the generalized polarizability function introduced for the EELS description, $\vec{p}_{i\perp}(\Omega)$ is the transverse dipole of mode i and $TF_z\left(\vec{E}_i^z\left(\vec{R}_{\perp}, \frac{\omega}{v}\right)\right)$ the Fourier transform along the e-beam direction at impact point $\vec{R}_{\perp} = (x, y)$ in real space and momentum $k_z = \omega/v$ in reciprocal space of the electron induced electric near field \vec{E}_i^z .

- Within a TF_z , CL maps spectrally and spatially the zEMLDOS, i.e. the electromagnetic density of states in the direction along the e-beam axis
- CL probability is proportional to the induced dipole $\vec{p}_{i\perp}$ + interference terms between mode orders (i, j)



Cathodoluminescence, a tool for near field optics

Instrumentation – SEM CL (a few 10 kV) , STEM CL (a few 100 kV)



➤ Scanning (transmission) electron microscope in cathodoluminescence mode - (electron in, photon out) process

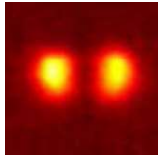
.Electron source (electron field gun)

.Electron optics, Electron energy = Tens of keV for a SEM, hundreds of keV for a TEM

.The electron beam is focused and raster scanned on the sample. Beam diam. $\varnothing \approx 10$ nm

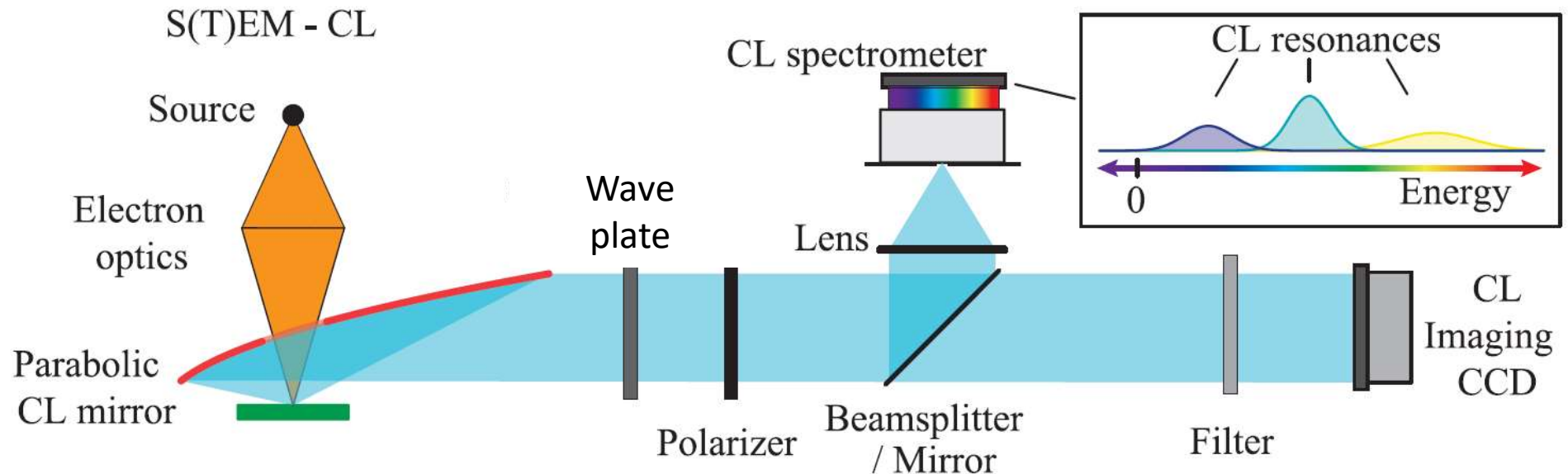
.The optical luminescence spectrum is collected using a parabolic mirror at each beam position (x, y)

➤ Near field imaging through the mapping of a cathodoluminescence signal



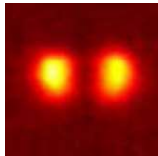
Cathodoluminescence, a tool for near field optics

Instrumentation – SEM CL (a few 10 kV) , STEM CL (a few 100 kV)



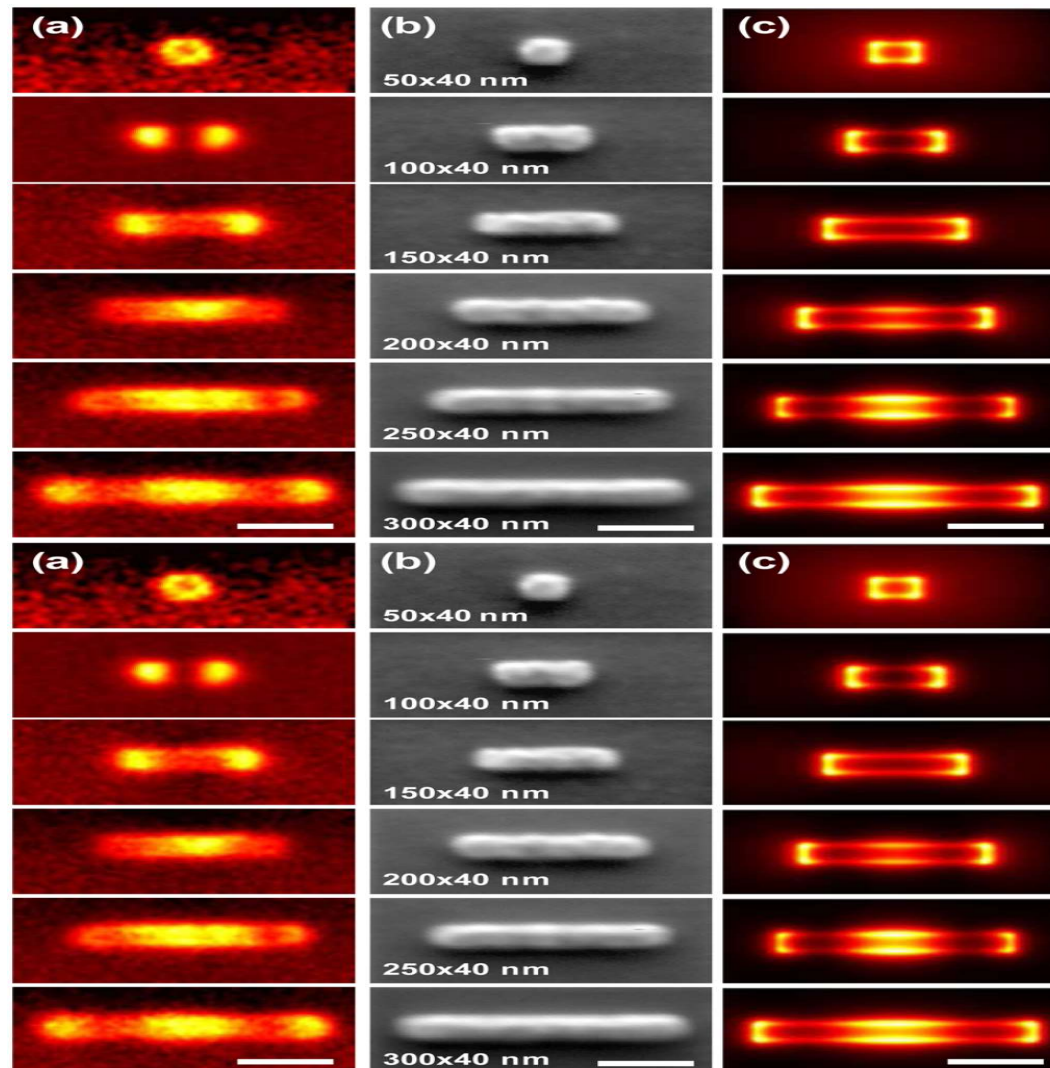
➤ Scanning (transmission) electron microscope in cathodoluminescence mode

- ◆ CL imaging mode. Acquisition of the spatially resolved cathodoluminescence signal at a particular optical wavelength λ . Spatial resolution $\delta R \approx$ electron beam diameter ≈ 10 nm
- ◆ CL spectrometry. Acquisition of a CL spectrum $I_{CL} = f(\lambda)$ at a fixed position (x, y)
CL signal spectral resolution 1 - 10 meV \Leftrightarrow 0.3 – 3 nm @ 600 nm
Significant broad luminescence background (post treatment analysis required)
- ◆ Optical signal = Additional information available like the polarization of the emitted light

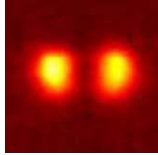


Plasmonics of Nanoobjects - NanoRods

Cathodoluminescence near field imaging – STEM CL (x,y) mode



Al nanorods (a) CL near field imaging for energy range 2.5 – 3.0 eV
(b) SEM images (c) Calculated electromagnetic field distribution (FDTD)



Cathodoluminescence, a tool for near field optics

CL near field mapping - Advances & Variants

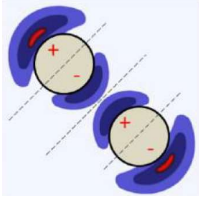
- ◆ CL 3D tomography

- Reconstruction of 3D CL intensity maps *A. C. Atre et al. Nat. Nanotechnol. 10 (2015) 429*

- ◆ Angle resolved CL imaging polarimetry

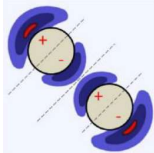
- Ability to characterize both directionality and polarisation characteristics of CL emission in the hemisphere above a plasmonic structure *B. J. M. Brenny et al. Appl. Phys. Lett. 107 (2015) 201110; C. I. Osorio et al. ACS Photonics 3 (2016) 147*

- ◆ Time resolved CL experiment, but in the ps time range (2019), not so relevant for plasmonics (1 - 10 fs time range)



Photon-Induced Near-Field Electron Microscopy

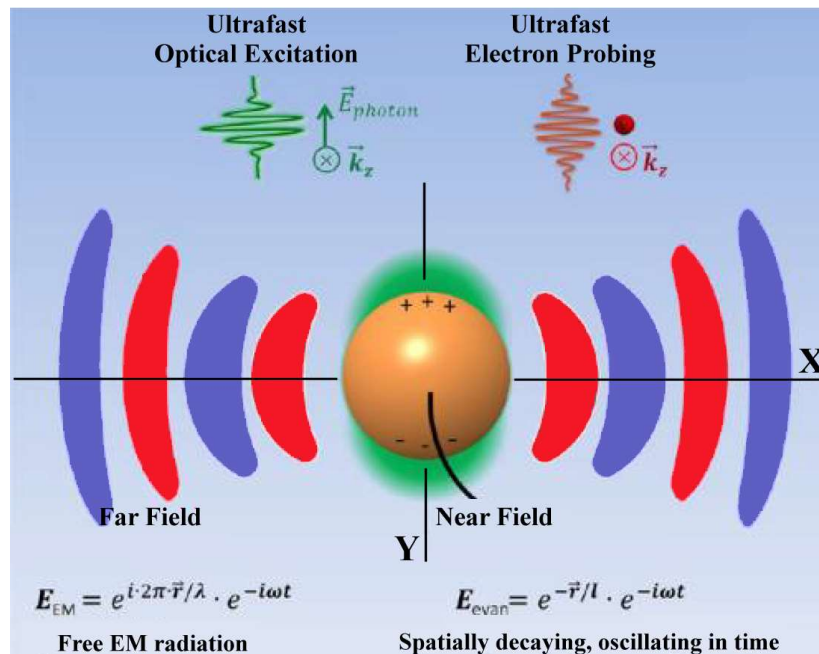
PINEM, a tool for near field optics



Photon-Induced Near-Field El. Micros., a tool for near field optics

Basic principle – PINEM near field imaging

- In PINEM, the plasmonic sample is excited with a photon pulse of femtosecond duration and, simultaneously, an ultrashort electron pulse images the near field induced using the optical excitation ⇒ **Three body interaction ($\hbar\omega$, plasmon, e^-)**



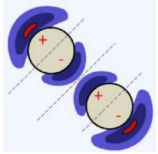
➤ Three body interaction

In free space, photons and electrons interact weakly because of a large momentum mismatch

$$e^- \text{ viewpt} \quad \Delta p(e^- + n \cdot \hbar\omega) = n \cdot \hbar\omega / v_e$$

$$\hbar\omega \text{ viewpt} \quad \Delta p(e^- + n \cdot \hbar\omega) = n \cdot \hbar\omega / c, \quad c > v_e$$

In solids, possible interaction between electrons and photons through a plasmon exchange, an additional source of energy and momentum - **Evanescent wave**, $\Delta z \cdot \Delta p \sim \hbar/2$

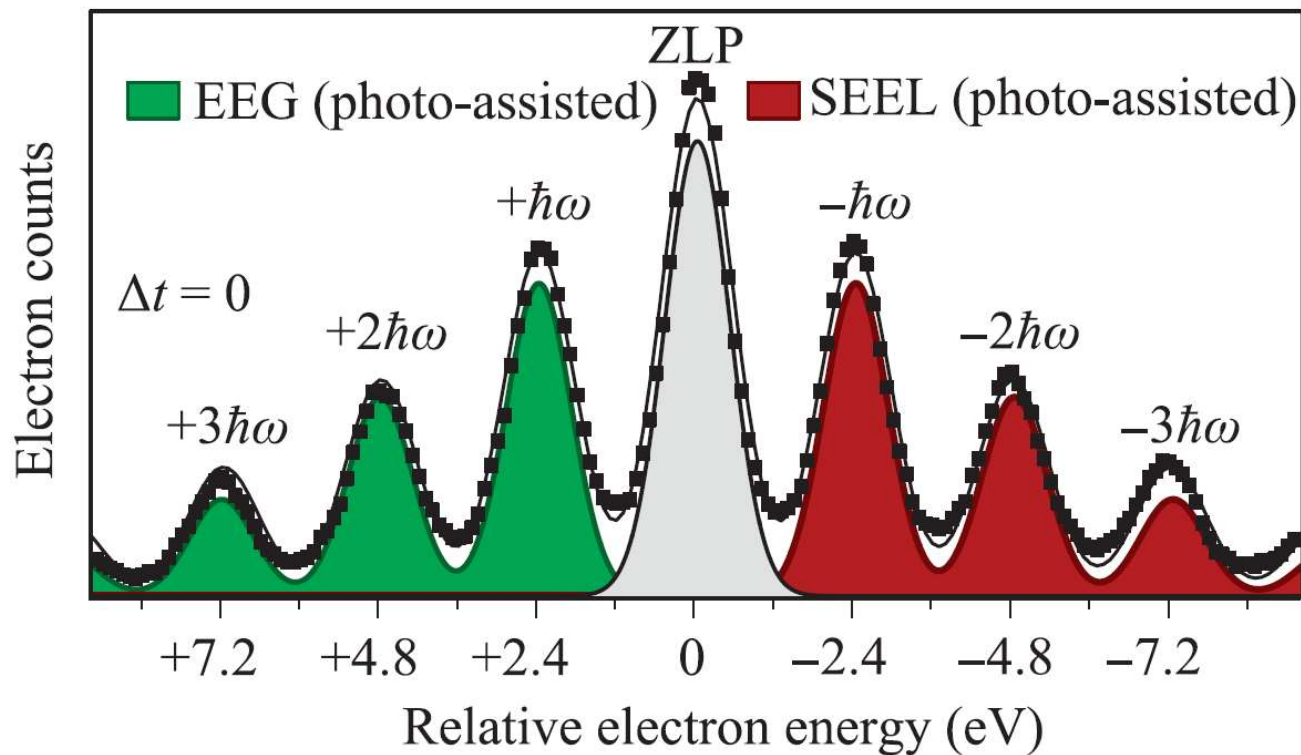


Photon-Induced Near-Field El. Micros., a tool for near field optics

Basic principle – PINEM near field imaging

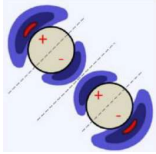
➤ Energy Electron Gain Spectrometry EEGS

In this three body interaction scheme, the electron packets **lose** and/or **gain energy** in discrete quanta of the photon energy $\hbar\omega$, because of the presence of a time oscillating electric field, the evanescent field associated with the resonant plasmon of the particle



Carbon nanotubes, electrons of 200 keV, fs lifetime
photons of 2.4 eV, fs lifetime
Full temporal overlap $\Delta t(\hbar\omega, e^-) = 0$ s

B. Barwick, D. Flannigan, A. Zewail *Nature* **462** (2009) 902
A. Yurtsever, A. Zewail *Nano Lett.* **12** (2012) 3334



Photon-Induced Near-Field El. Micros., a tool for near field optics

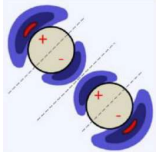
Basic principle – PINEM probability for a small sphere Γ_{EEGS}

$$\Gamma_{EEGS}^{sphere}(\omega, R_{\perp}) \propto \left(\frac{\omega}{\gamma v^2}\right)^2 I_0 |\alpha_{l=1}(\omega)|^2 K_1^2\left(\frac{\omega R_{\perp}}{\gamma v}\right) \delta(\omega - \omega_{ph.})$$

$$\Gamma_{EEGS}^{sphere}(\omega, R_{\perp}) \propto \left(\frac{\omega}{\gamma v^2}\right)^2 I_0 |\alpha_{l=1}(\omega)|^2 \delta(\omega - \omega_{ph.}) \exp\left(-\frac{R_{\perp}}{\gamma v/\omega}\right)$$

I_0 Intensity of the excitation laser; $R_{\perp} = (x, y)$ Impact parameter of the electrons traveling along the z direction at speed v ; $\hbar\omega$ Loss energy; $\hbar\omega_{ph.}$ photon energy; γ Lorentz factor $\gamma = 1/\sqrt{1 - v^2/c^2}$ (relativistic electrons); K_m Modified Bessel function of the second kind; α_l Sphere polarizability for mode $l = 1$

- PINEM probability of a small sphere is proportional to its scattering cross section as measured in far field optics, $\sigma_{sca.} \propto |\alpha_{l=1}(\omega)|^2 \propto a^6$
- PINEM probability is position-dependent with a quasi-exponential decay with e-beam to sphere distance R_{\perp} , attenuation length $\gamma v/\omega \sim 10 - 100$ nm
- PINEM proceeds by discrete quantum energy exchange $\delta(\omega - \omega_{ph.})$



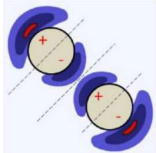
Photon-Induced Near-Field El. Micros., a tool for near field optics

Basic principle – PINEM vs EMLDOS

- By energy-filtering only those electrons resulting from **one specific photon absorption**, it is possible to :
 - image directly in space the electric nearfield distribution
 - obtain the temporal behavior of the field on the femtosecond timescale
 - map its spatial polarization dependence – **Polarisation control (bright modes)**
- Similar to CL and EELS, within a Fourier transform PINEM detects the near electric field component along the direction of the electron beam

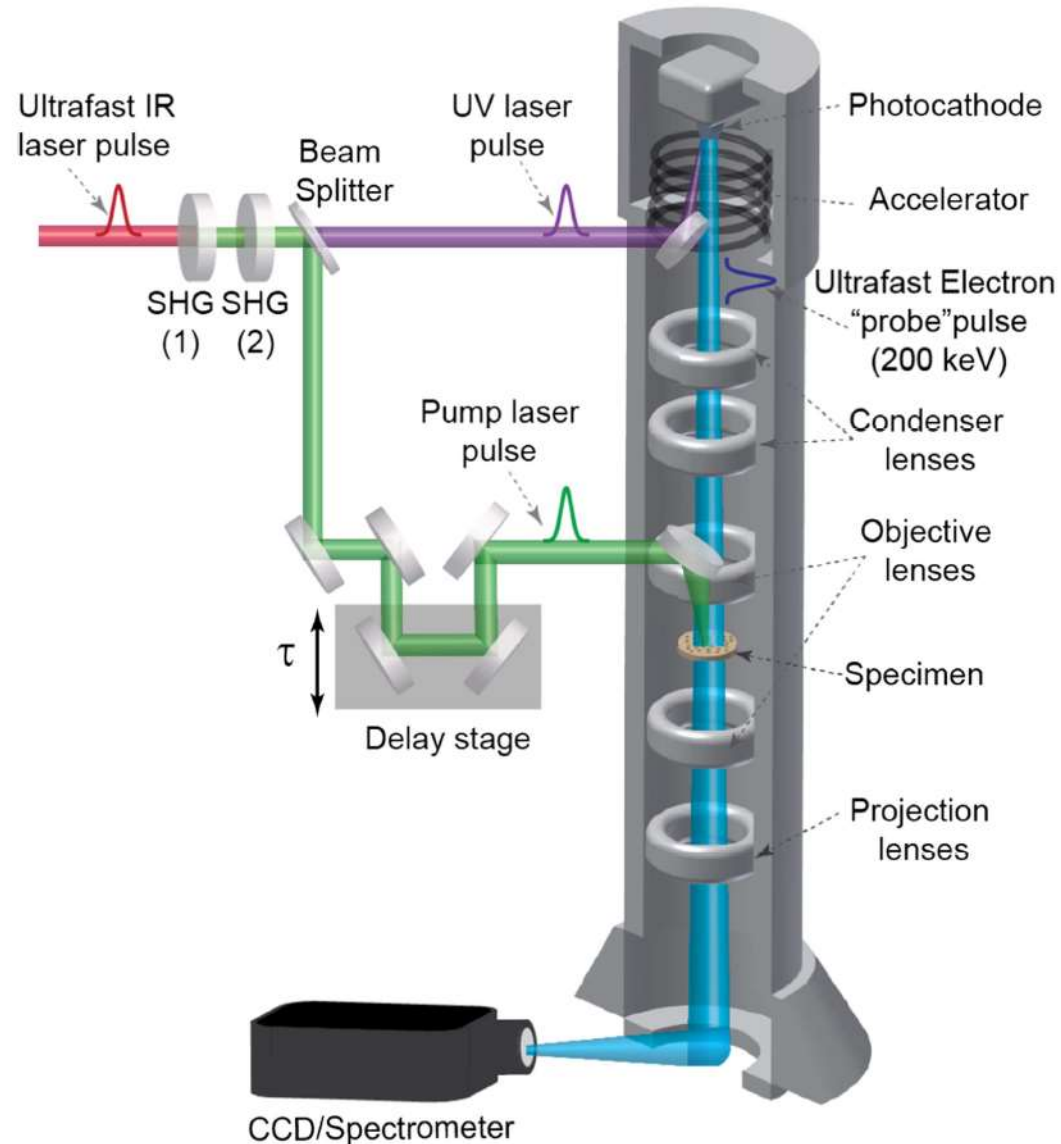
$$I_{\text{PINEM}}(x, y, \Delta t) = \left| \int_{+\infty}^{-\infty} E_z^{\text{photon}}(x, y, z, \Delta t) e^{-i\left(\frac{\omega}{v}\right)z} dz \right|^2$$

Fourier transform the E_z^{photon} photon induced electric nearfield, along the e-beam direction at point $\vec{R}_\perp = (x, y)$ in real space, momentum value $q_z = \omega / v$ in reciprocal space and time delay Δt between electron and photon pulses (power spectrum)

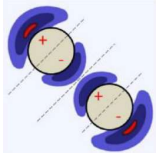


Photon-Induced Near-Field El. Micros., a tool for near field optics

Instrumentation – Ultrafast Electron microscope UEM

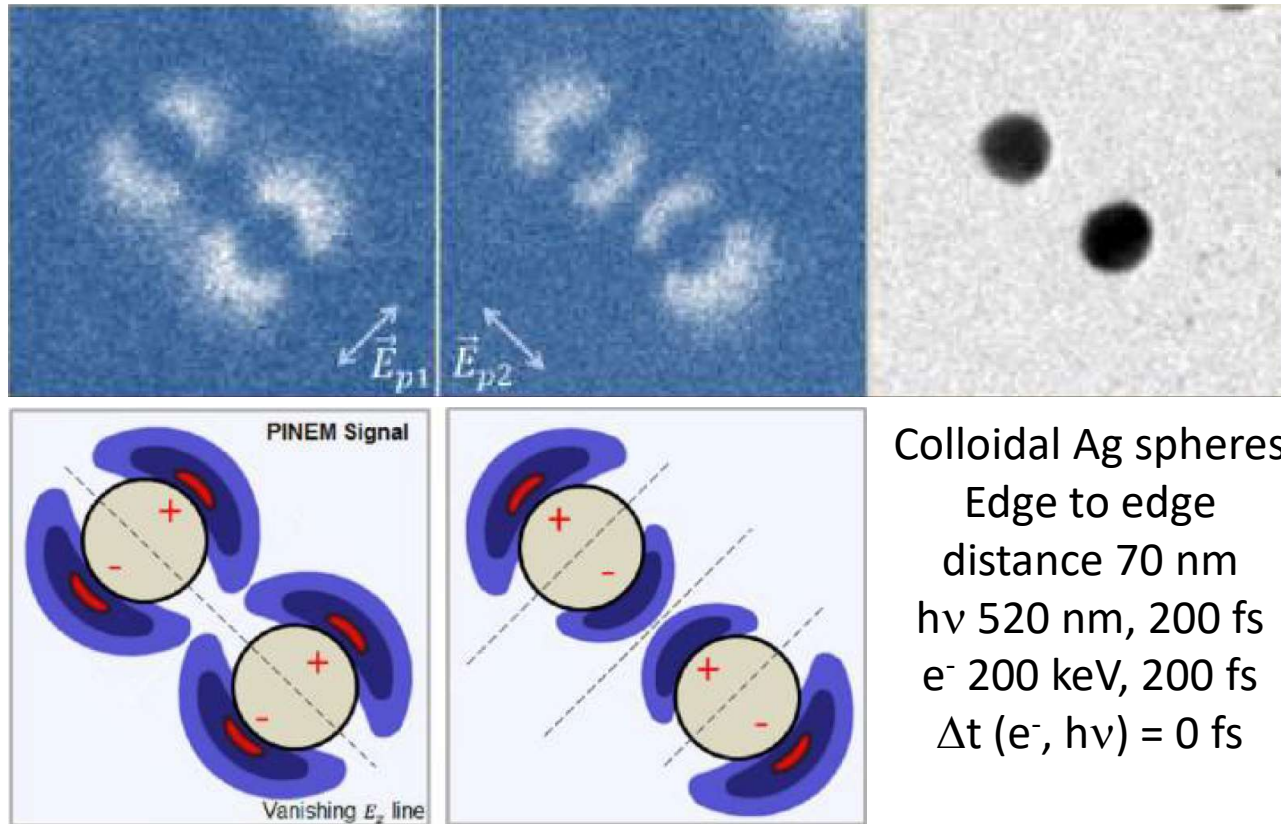


(photon in,
electron in,
electron out)
process

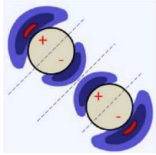


PINEM near field imaging

Plasmonics of 0D objects - Au NanoSpheres

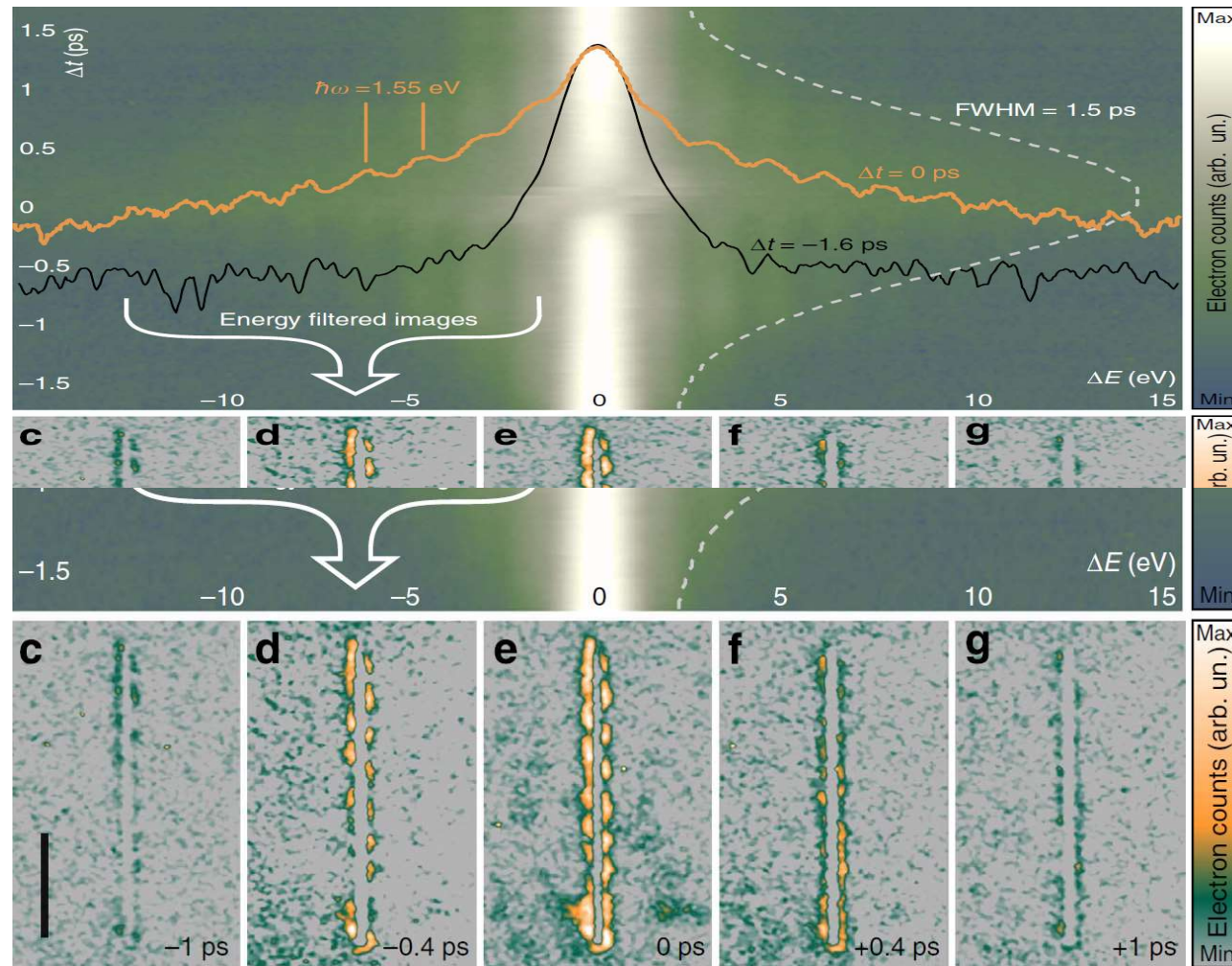


- Near field electric field mapping along the direction of the electron beam E_z
- Spatial polarization dependence – **Optical Polarisation Control**

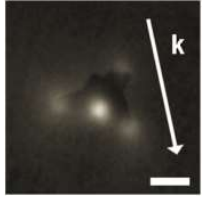


PINEM near field imaging

Plasmonics of 1D objects – Ag Nanowires $5.7 \mu\text{m} \times 0.134 \mu\text{m}$

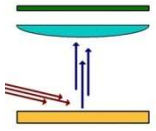


➤ Electron intensity map vs the time delay Δt between the optical pump and electron probe pulses. Wavelength 800 nm, polarization angle 45° . (c – g) Pictures of a single Ag nanowire at different Δt obtained using EEG electrons (white arrow). Scale bar $2 \mu\text{m}$.



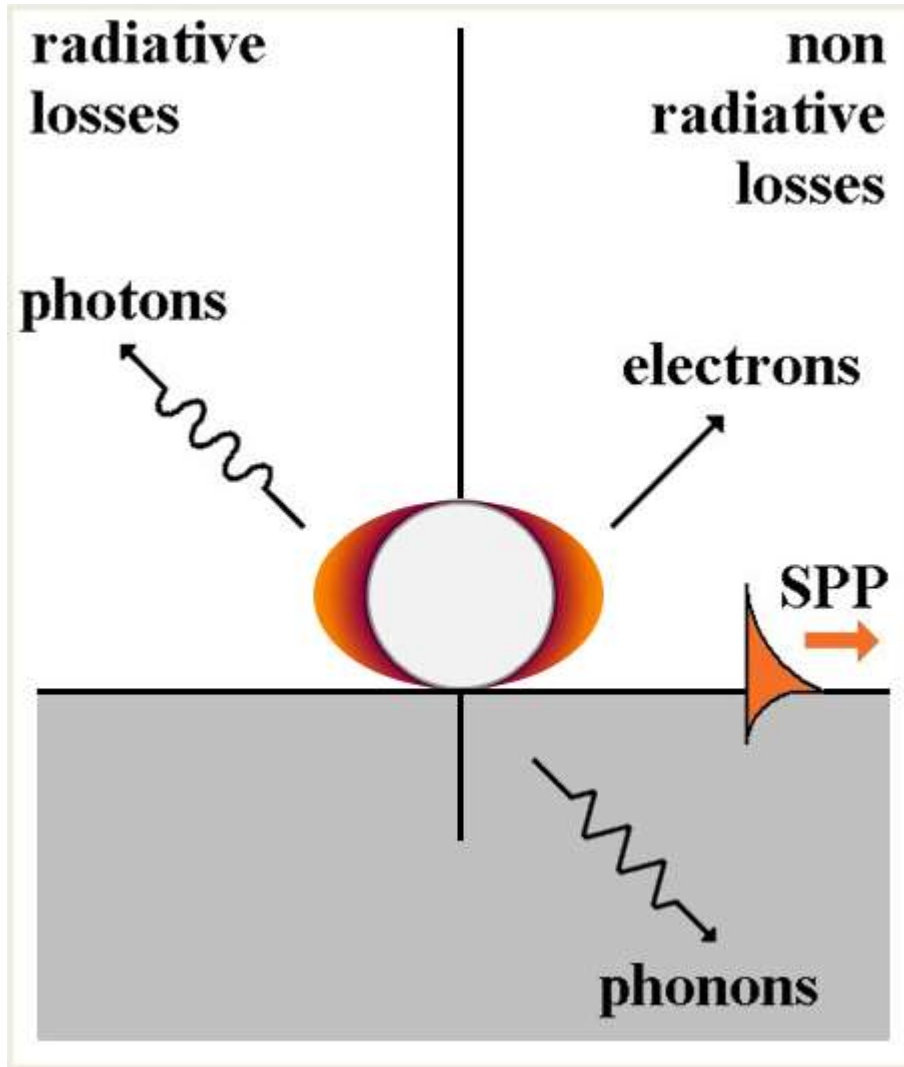
Photoemission electron microscopy PEEM

A tool for near field optics



Photoemission electron microscopy, a tool for near field optics

Basic principle – Plasmon decay channels



➤ Plasmon decay channels

.free-space radiative losses

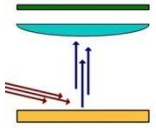
scattering
luminescence

.non radiative losses

ohmic losses (phonons)
secondary SPP excitation
electron emission

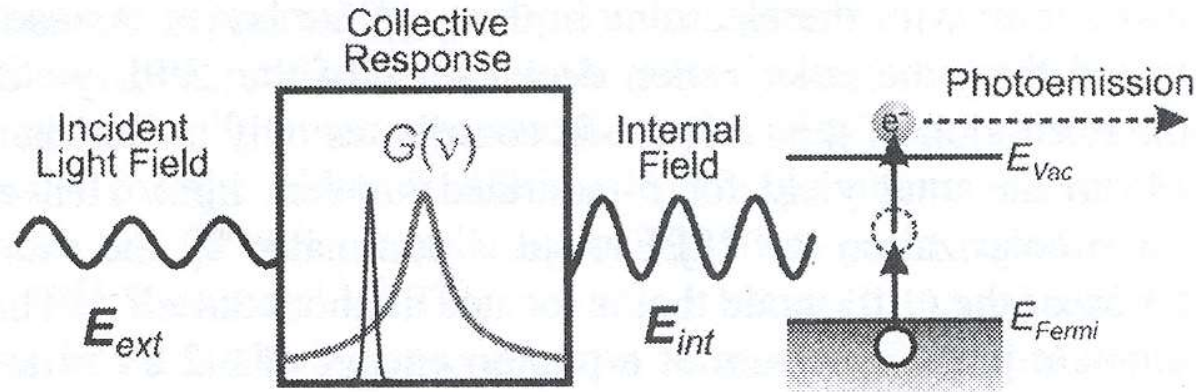
...

➤ Mapping the near field at the nanoscale through electron emission - Photoelectric effect



Photoemission electron microscopy, a tool for near field optics

Physical principle



(i) Plasmon excitation \Leftrightarrow Exalted photoelectric effect in plasmonic field

(ii) Non linear photoemission process

Plasmon res. $E_{\text{plasmon}} \approx 1,55 \text{ eV}$ (IR 800 nm)

Metal work function $\Phi_{\text{metal}} \approx 4,5 \text{ eV}$

$$E_{\text{int.}}(\nu) = G(\nu) \cdot E_{\text{ext.}}(\nu), \quad G_{\text{Sphere}} = \frac{3\epsilon_m}{\epsilon + 2\epsilon_m}$$

$$n \cdot h\nu > \Phi_{\text{Metal}}$$

$E_{\text{int.}}$ Internal electric field [V/m]

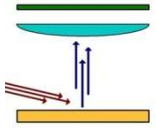
G Response function of the many electron system

$E_{\text{ext.}}$ Incident electric field [V/m]

n order of non linearity,

$h\nu$ photon energy [eV],

Φ_{metal} metal work function [eV]



Photoemission electron microscopy, a tool for near field optics

Basic principle

- The non linear photoemission process is proportional to the $2n^{\text{th}}$ power of the surface electric field $E_{\text{int.}}$ (electron reservoir, surface photoemission process)
- Multiphotonic cascade absorption and/or coherent absorption from a hot electron gas

$$I_{e^-} \propto (\vec{p} \cdot \vec{E}_{\text{int.}})^{2n} \propto (\vec{p} \cdot G \vec{E}_{\text{ext.}})^{2n}$$

p electron momentum [kg.m/s]

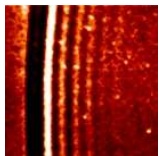
$E_{\text{int.}}$ internal electric field [V/m]

n non linearity order

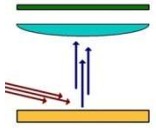
$E_{\text{ext.}}$ incident electric field [V/m]

- Bright field modes accessible (**photon in**)
- Near field dynamics

For large objects $\geq \lambda_{h\nu}$, the internal electric field of the plasmon excitation $\vec{E}_{\text{int.}}^{SPP}(r, t)$ (group velocity $v_{SPP} < c$) interferes with a 2^{nd} component linked to the incident field $\vec{E}_{\text{int.}}^{h\nu}(r, t)$ (group velocity c / refractive index).



- For large objects $\geq \lambda_{h\nu}$, observation of beating interference patterns between $(\vec{E}_{\text{int.}}^{SPP}(r, t), \vec{E}_{\text{int.}}^{h\nu}(r, t))$



Photoemission electron microscopy, a tool for near field optics

Basic principle – Photoelectron emission rate R_{Emission}

$$R_{\text{Emission}}^{\text{Surface}} \approx \frac{2}{\pi^2} \frac{e^2 E_F^2}{\hbar} \frac{1}{(\hbar\omega)^3} \int_{\text{Surface}} |E_{\text{Surf.int.}}^\perp|^{2n} dS$$

R_{Emission} electron emission rate [electrons/s]

e electron charge [C]

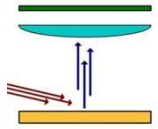
$\hbar\omega$ energy of the incident photon [eV]

E_F Fermi level of the metallic particle [eV]

n non-linearity order, *i.e.* the number of photons absorbed to overcome the work function of the specimen []

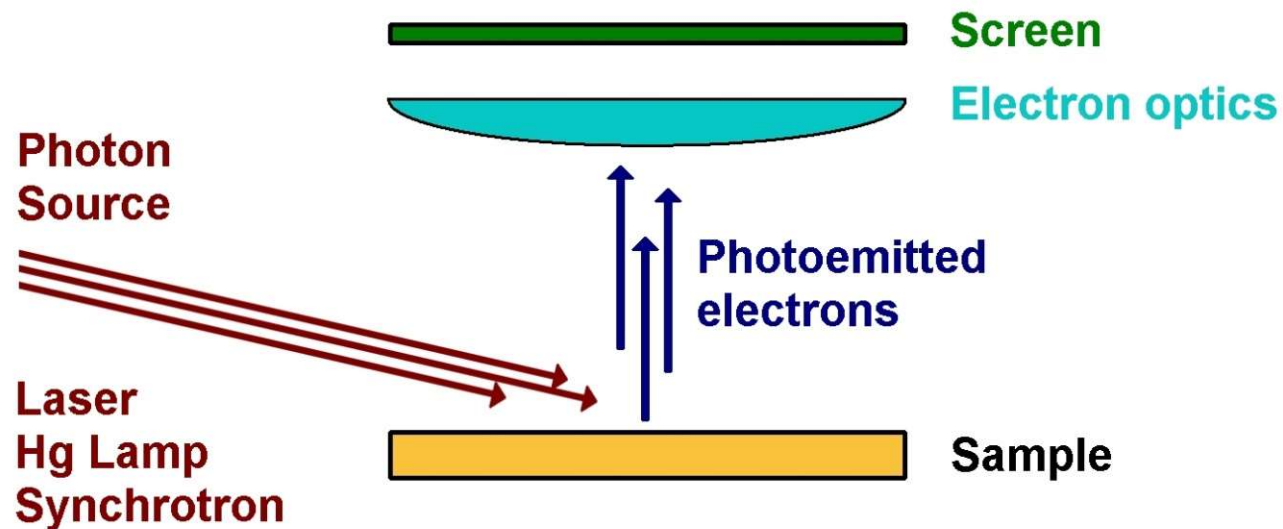
$E_{\text{Surf.int.}}^\perp$ normal to the surface component of the near electric field, *i.e.* EMLDOS $_\perp$
electromagnetic density of states along the normal of the object surface [V/m]

➤ PEEM signal scales with the electromagnetic density of states projected on the object surface normal.



PEEM – photoemission electron microscopy (1933)

Instrumentation



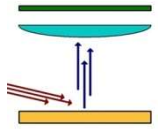
➤ **Basic principle. Mapping of the photoemitted electron distribution in two dimensions (photon in, electron out)**

- .standard electron optics (electrostatic, magnetic lenses)
- .full field microscopy, no scanning probe
- .non intrusive technique, no physical tip in the vicinity of the measuring volume (\neq SNOM)

.image contrast: work function Φ (small photon $h\nu$), photoemission lines (large photon $h\nu$)

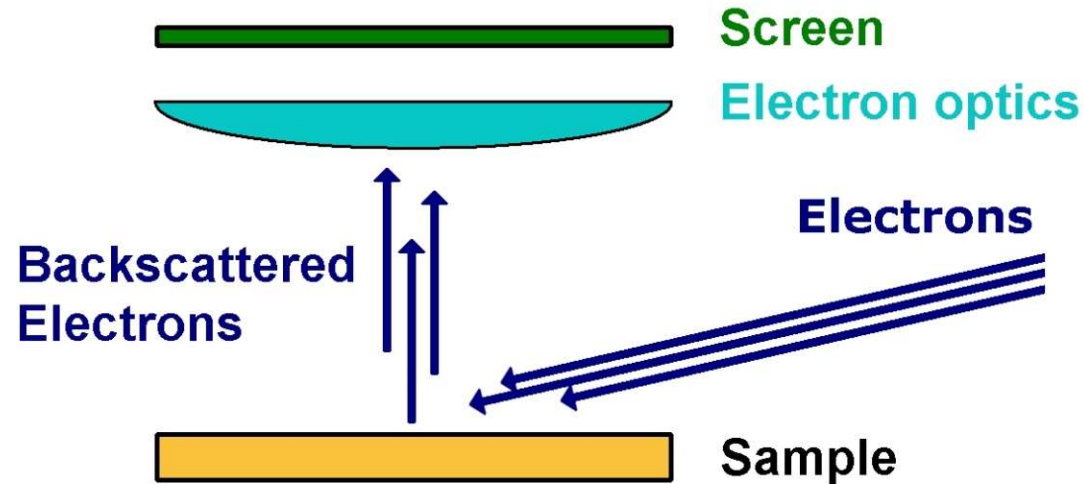
.surface sensitivity \sim electron inelastic mean free path $\lambda_{\text{electron}}$

.lateral resolution (16 / 84 criteria) \approx **20 nm, resp. \leq 5 nm on AC instrument**



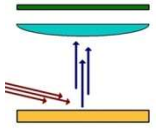
LEEM – low energy electron microscopy

Instrumentation



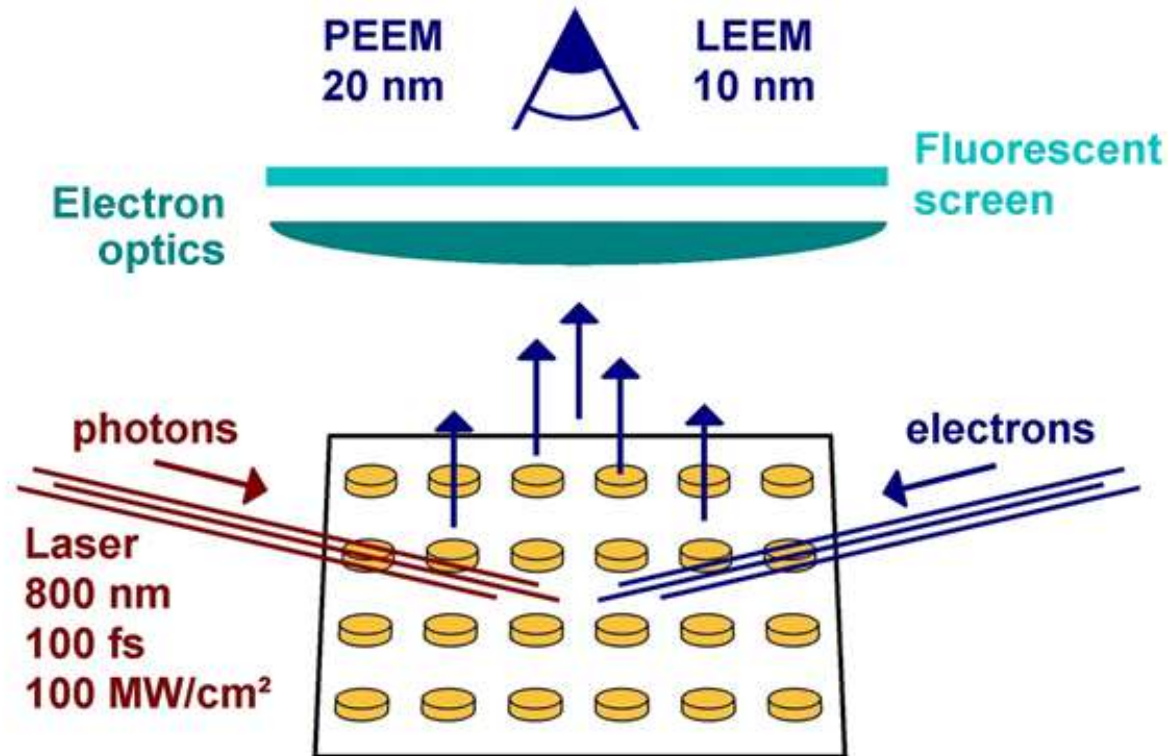
- **Basic principle. Mapping of the 2D backscattered electron distribution (electron in, electron out)** - Topographic imaging LEEM = TF(LEED + phase)
 - .standard electron optics (electrostatic & magnetic lenses)
 - .full field microscopy, no scanning probe
 - .non intrusive technique, no physical tip in the vicinity of the measuring volume

 - .contrast = diffraction, interferences between optical electron paths...
 - .vertical resolution = atomic step
 - .lateral resolution (16/84 criteria) \approx **10 nm, resp. \leq 2 nm on AC instrument**

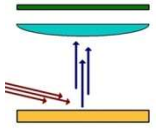


Mapping the evanescent field at the nanometre

LEEM/PEEM instrument (CEA IRAMIS Saclay)

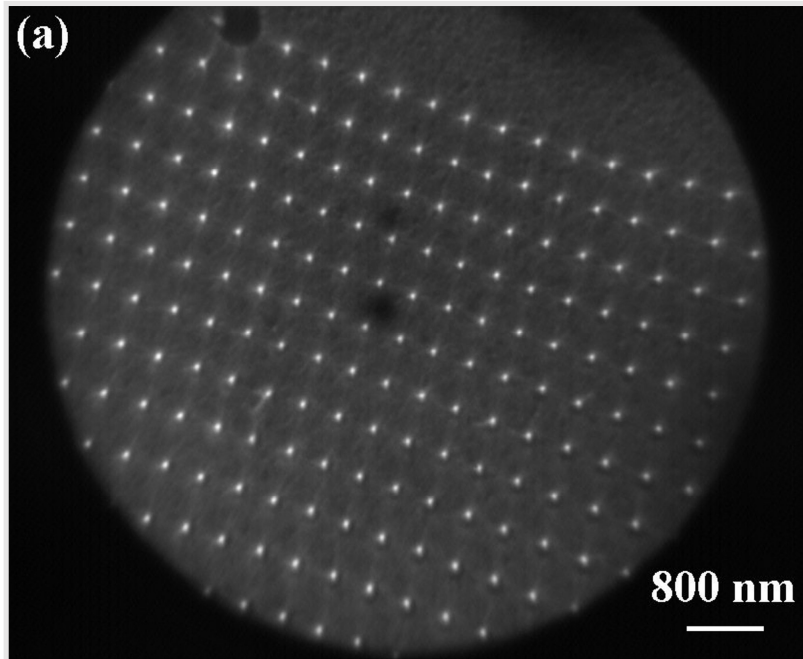


- Conductive sample (no charging effect) of low roughness
- LASER source Ti:Al₂O₃, 150 fs, wavelength [680 nm, 1100 nm] (IR) + OPO wavelength [525 nm, 650 nm], incidence angles {-90°, -45°, +3°, +15°, +90°} / sample surface plane
- LEEM / PEEM III equipped with an electron energy analyser www.elmitec-gmbh.com
 - PEEM field of view 1.5 - 120 μm, 16/84 lateral resolution **20 nm** (≤ 5 nm AC)
 - LEEM field of view 1.5 - 80 μm, 16/84 lateral resolution **10 nm** (≤ 2 nm AC)



Mapping the evanescent field at the nanometre - PEEM

Nanoparticle assemblies - LSP

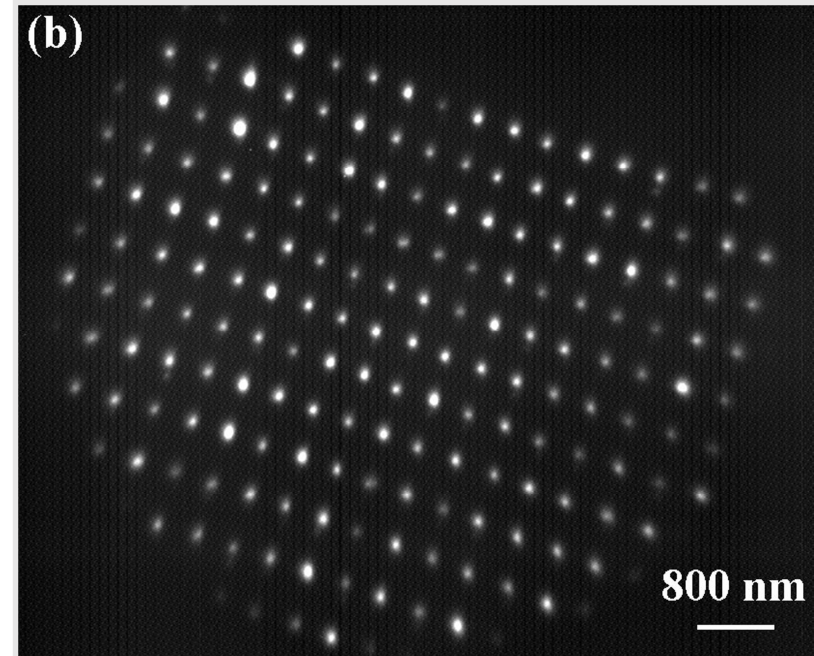


Au disks / ITO - \varnothing 120 nm, lattice spacing 400 nm
Source UT Troyes

➤ **LEEM picture (topographic imaging mode)**

Excitation = electrons (LASER off)

Signal = backscattered electrons



Au disks / ITO - Grazing incidence p pol. 150 MW/cm²

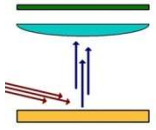
➤ **PEEM picture under LASER illumination**

Excitation = 766 nm photons

$h\nu$ (1.62 eV) < Φ_{Au} (4.6 - 5.1 eV)

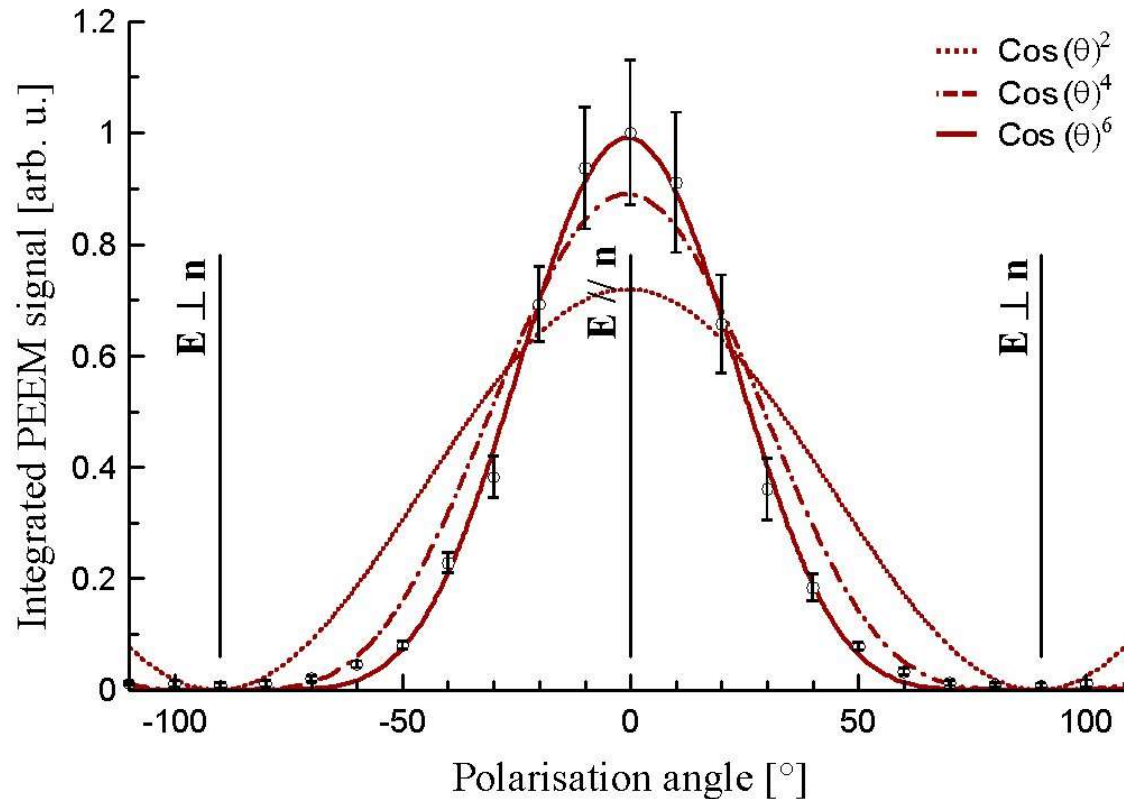
Signal = photoelectrons ! (3 $h\nu$ / e^-)

High signal to noise ratio



Non linear photoemission – PEEM

Nano-particle assemblies – Off plane polarisation dependence



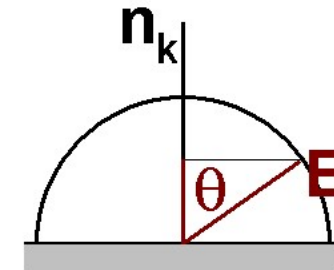
Au disks / ITO \varnothing 120 nm

grazing incidence 17°

photon 880 nm (1.41 eV)

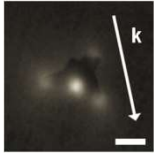
power dens. 140 MW/cm²

Keldysh factor 36 \gg 1



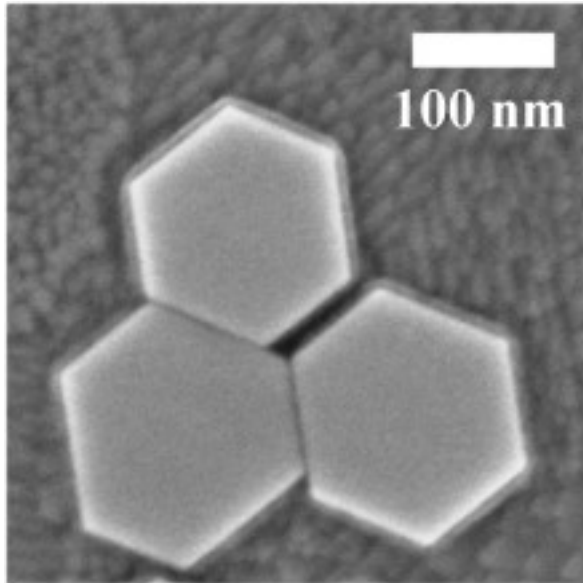
➤ Dependence of the photoemission yield with the polarisation angle θ at grazing incidence \Leftrightarrow PEEM integrated signal scales as $\cos(\theta)^6$

➤ **3 photon photoemission process** ($3 \times 1.41 \text{ eV} = 4.23 \text{ eV}$, $\Phi_{\text{Au}} \approx 4.6 - 5.1 \text{ eV}$). Probable field assisted 3-PPE emission mechanism.



Plasmonics of 2D objects - Nanohexagon D_{6h} - PEEM

Near field mapping - Linear polarisation

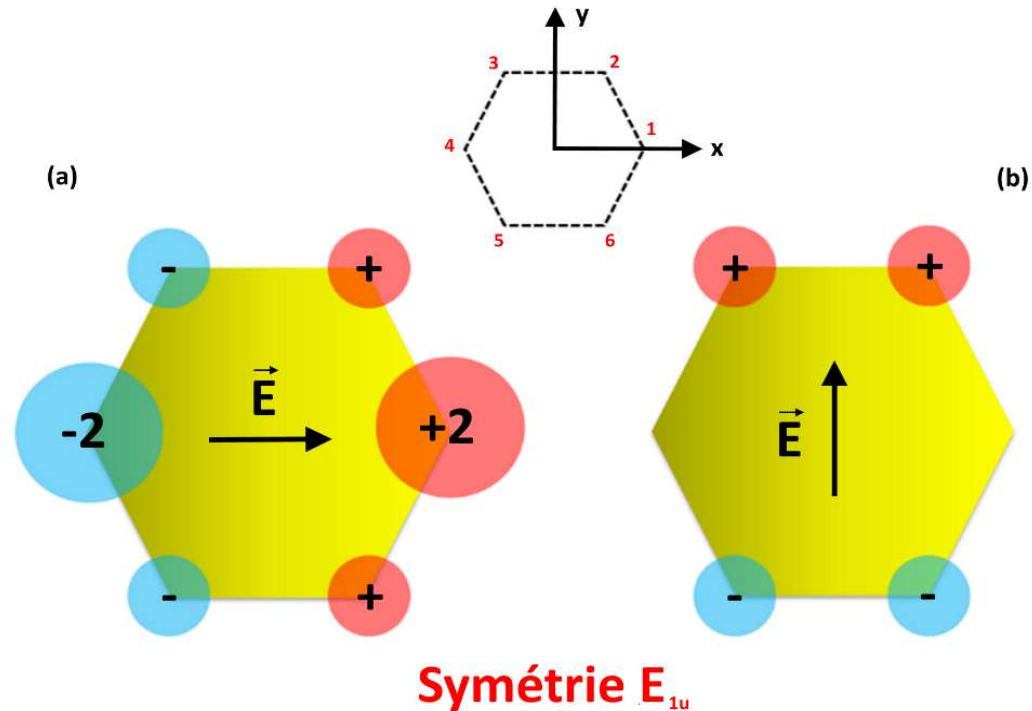


Au Hexagon - SEM

$L = 150 - 200 \text{ nm}$

Thickness $\approx 15 \text{ nm}$

(Colloïdal synthesis, CEA S. Marguet)



➤ Group Theory

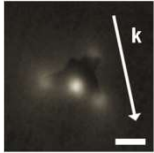
Hexagon = Object of D_{6h} symmetry

Eigenstates of the dipolar plasmon resonance
for a linear polarisation excitation

S. Mitiche PhD (2018)

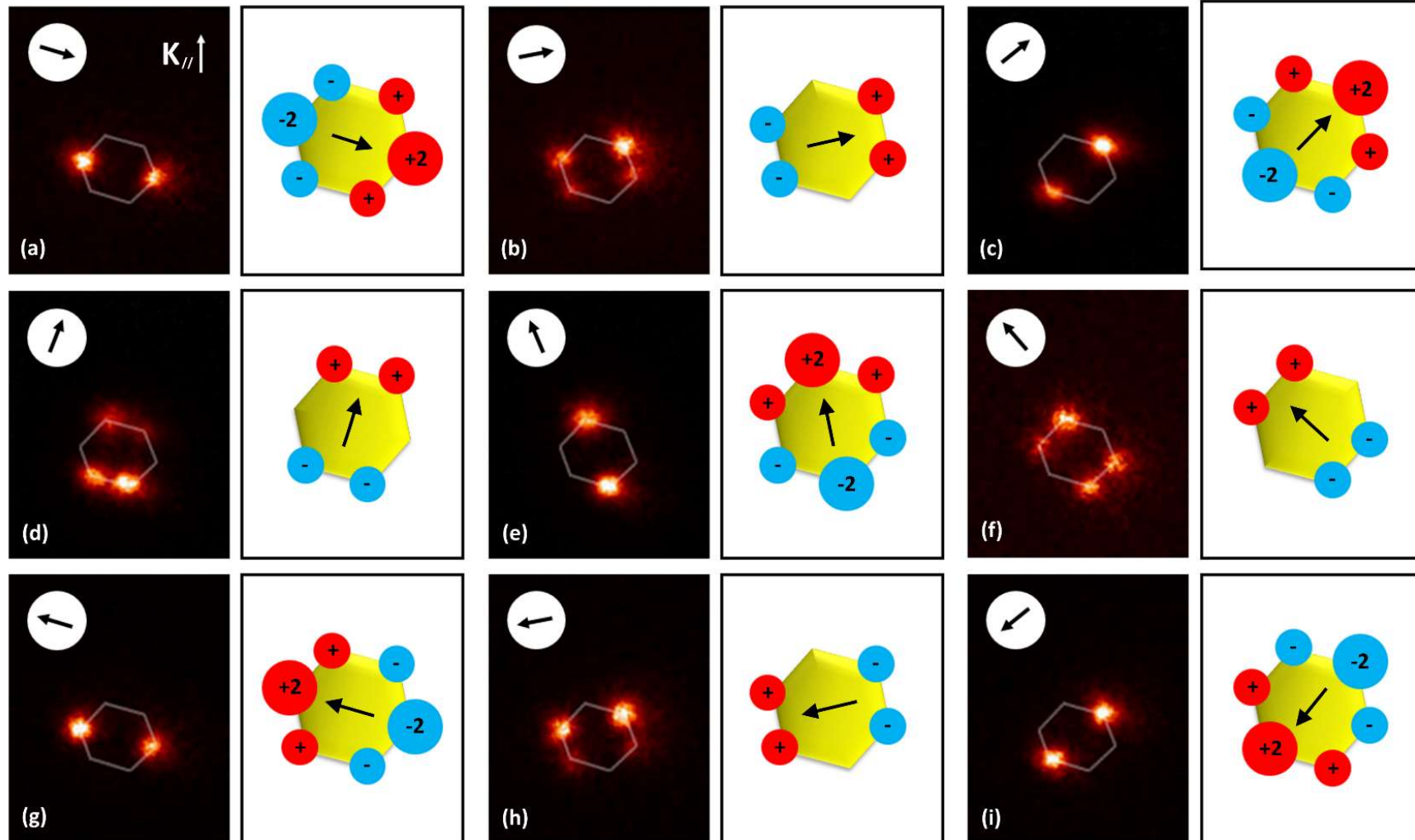
S. Mitiche, *et al. J. Phys. Chem. C* **121** (2017) 4517

C. Awada, T. Popescu *et al. J. Phys. Chem. C* **116** (2012) 14591

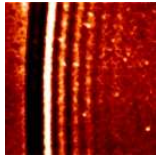


Plasmonics of 2D objects - Nanohexagon D_{6h} - PEEM

Near field mapping - Linear polarisation

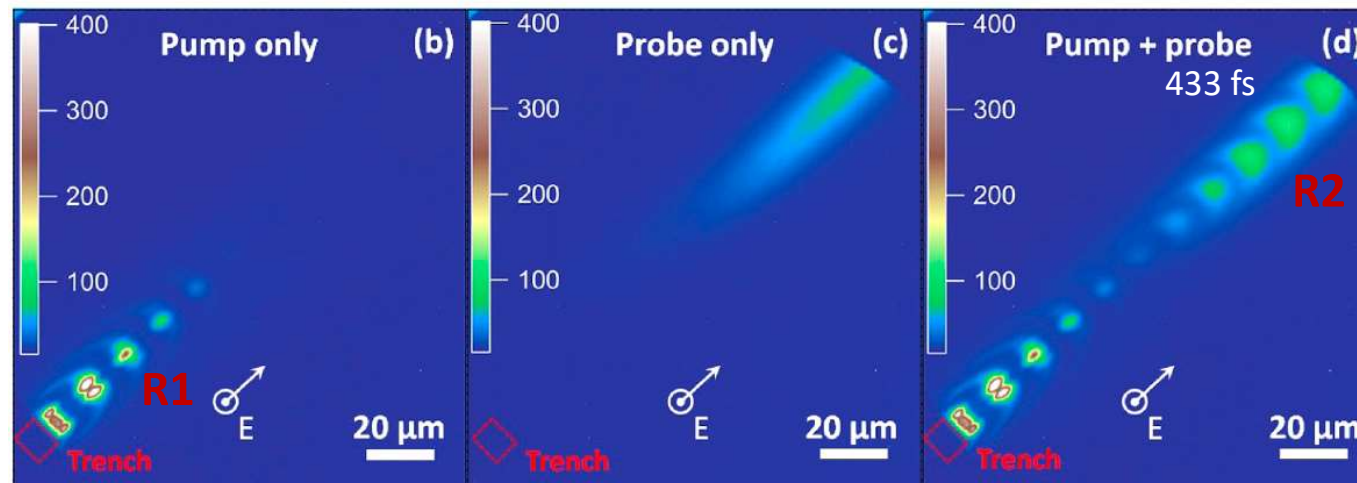
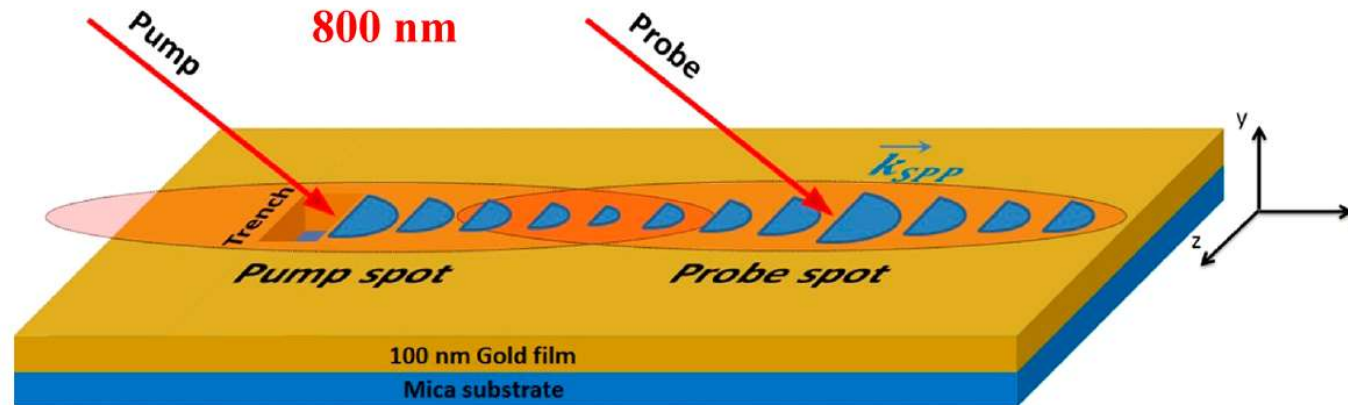


- 150 nm Au Hexagon – Dipolar resonance ($\lambda = 850$ nm) under linear pol. exc.
PEEM Imaging & Group Theory Interpretation (S. Mitiche PhD 2018)



Propagation of plasmons-polaritons (nm, fs) – PEEM

2D Symmetry – Pump-probe experiment - Au / vide interface

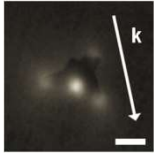


➤ Plasmon propagation from a trench in a Au film (\vec{k} conservation)

Pump-probe experiment. Time resolution = 0,2 fs, spatial resolution = 20 nm

Field propagation length $\delta(\text{Au}, 800 \text{ nm}) = 88 \mu\text{m}$ (92 μm JC72, 89 μm Ordal87)

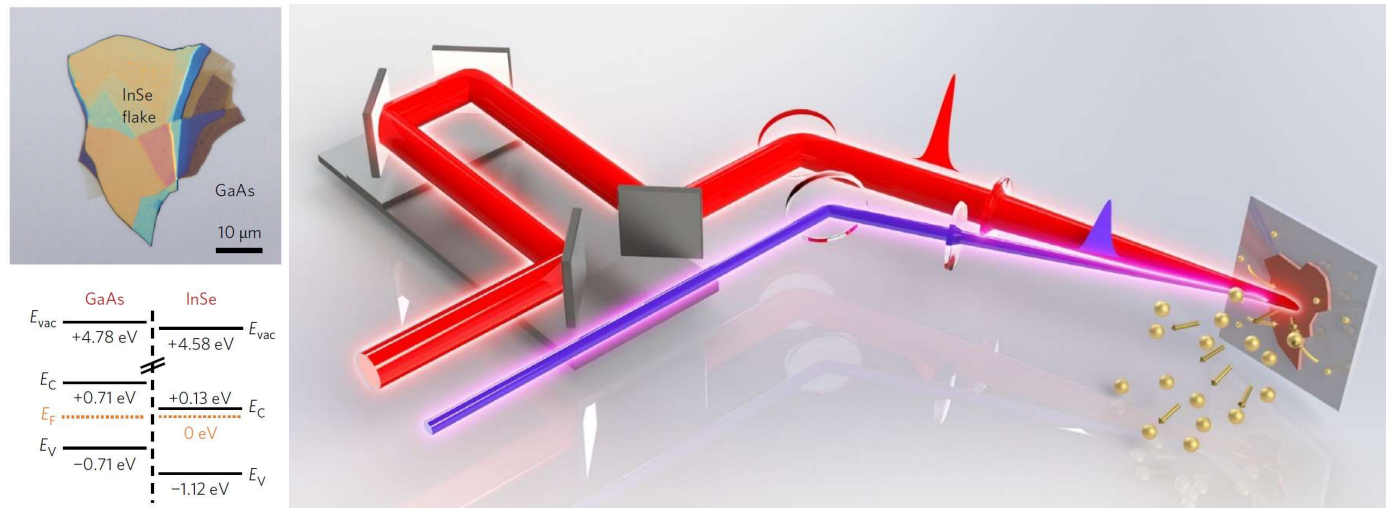
Group velocity SPP = 0,95c



Photoemission electron microscopy, a tools for nanooptics

PEEM near field mapping - Advances & Variants

- ◆ Time-resolved PEEM experiment, one or two colours. M. Man *et al. Nature Nanotech* **12** (2017) 36



- ◆ Multiscale approaches in spatial (nm), spectral (meV) and temporal domains (ns, ps, fs, as). A. Losquin, T. Ludden *Front. of Phys.* **12** (2017) 127301

- ◆ Technological developments

- Aberration corrections of the electron optics ($\Delta r \approx 1$ nm)
- Electron detectors (TemCam camera, Medipix)

Mapping the evanescent field at the nanometre with electrons

Alternative non intrusive methods

- STEM EELS *scanning transmission microscopy in electron energy loss spectro. mode* (electron in, electron out) = Mapping of an electron energy loss signature
- CL *cathodoluminescence* (electron in, photon out) related to EELS
- PINEM *photon-induced near-field electron microscopy* (electron in, photon in, electron out)
- PEEM *photoemission electron microscopy* (photon in, electron out), other acronym = n-PPE *n photon photoemission, time resolved TR-PEEM*

➤ Reference Reviews

A. Losquin, T. A. Lommen **Electron microscopy methods for space-, energy-, and time-resolved plasmonics** *Front. Phys.* **12** (2017) 127301, DOI [10.1007/s11467-016-0605-2](https://doi.org/10.1007/s11467-016-0605-2)

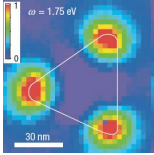
A. Merlen, F. Lagugné-Labarhet **Imaging the Optical Near Field in Plasmonic Nanostructures** *Applied Spectroscopy* **68** (2014) 1307-1326, DOI [10.1366/14-07699](https://doi.org/10.1366/14-07699)

M. Kociak, O. Stéphan **Mapping plasmons at the nanometer scale in an electron microscope** *Chem. Soc. Rev.* **43** (2014) 3865, DOI [10.1039/C3CS60478K](https://doi.org/10.1039/C3CS60478K)

T. Coenen *et al.* **Cathodoluminescence microscopy: Optical imaging and spectroscopy with deep-subwavelength resolution** *MRS Bulletin* **40** (April 2015) 359, DOI [10.1557/mrs.2015.64](https://doi.org/10.1557/mrs.2015.64)

L. Douillard, C. Charra **High-resolution mapping of plasmonic modes: photoemission and scanning tunnelling luminescence microscopies** *J. Phys. D: Appl. Phys.* **44** (2011) 464002, DOI [10.1088/0022-3727/44/46/464002](https://doi.org/10.1088/0022-3727/44/46/464002)

➤ Supplementary material



Electron Energy loss spectrometry, a tool for plasmonics

Basic principle – Electron energy loss spectrum

➤ Investigate the excitations of surfaces, thin films or objects using the inelastically diffracted / scattered electrons – Analysis of the electron energy losses

$$(E_i, k_i)_{electron} + excitation (fast electrons) \rightarrow (E_f, k_f)_{electron}$$

$$\Delta E(\vec{q}_{//}) = E_f(\vec{k}_f) - E_i(\vec{k}_i) \text{ Energy conservation}$$

$$\Delta \vec{k}_{//} = \vec{q}_{//} + \vec{G}_{//}, \vec{k}_{//} \text{ component momentum conservation}$$

Zero loss region – Low primary energies, high energetic resolution

$$E_i < 200 \text{ eV}, 1 \text{ meV} < \Delta E < 100 \text{ meV}$$

→ High Resolution Electron Energy Loss Spectrometry HREELS

Low loss region

$$E_i < 1000 \text{ eV}, 100 \text{ meV} < \Delta E < 50 \text{ eV}$$

→ Electron Energy Loss Spectrometry EELS

High loss region – High primary energies

$$\Delta E > 50 \text{ eV}$$

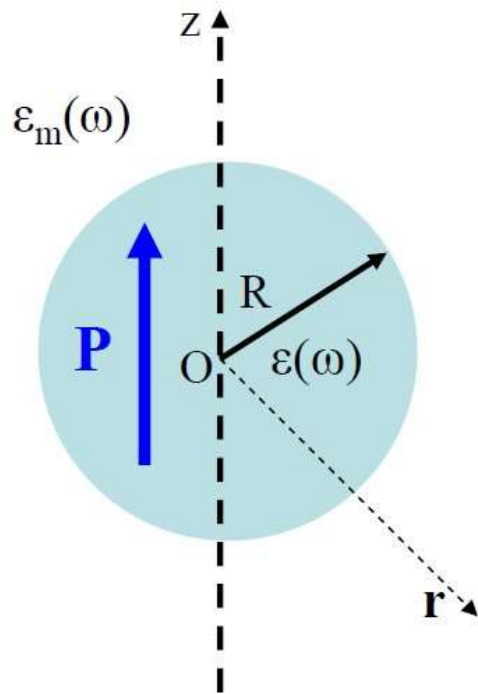
→ Extended Electron energy Loss Fine Structures EXELFS

Approximation dipolaire (ou quasistatique) : $\lambda \gg \text{Rayon}$ (effets de retard négligeables)

$$\vec{E} \uparrow \quad \vec{k} \rightarrow \quad \vec{E}_0 e^{i(\vec{k} \cdot \vec{r} - \omega t)} \quad \longrightarrow \quad \vec{E}_0 e^{-i\omega t}$$

toutes les grandeurs (\vec{E} , \vec{P} , \vec{D} , V) oscillent en ($\sim e^{-i\omega t}$)

$$\vec{E}(\vec{r}) = -\text{grad}[V(\vec{r})] \quad \Delta V(\vec{r}) = 0 \quad + \text{conditions aux limites} + \text{champ à grande distance } (\vec{E}_0)$$



Champ interne \vec{E}_{int} (et donc \vec{P}) uniforme

$$\vec{E}_{\text{int}} = \frac{3\epsilon_m}{\epsilon + 2\epsilon_m} \vec{E}_0 \quad \vec{P} = \epsilon_0 \chi \vec{E}_{\text{int}}$$

Champ externe

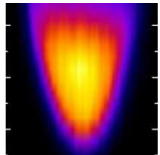
$$\vec{E}_{\text{ext}} = \vec{E}_0 - \underbrace{\text{grad} \left[\frac{1}{4\pi\epsilon_0\epsilon_m} \frac{\vec{m} \cdot \vec{r}}{r^3} \right]}_{\text{champ créé par un dipôle } \vec{m} \text{ placé en } O}$$

\Leftrightarrow champ créé par un dipôle \vec{m} placé en O

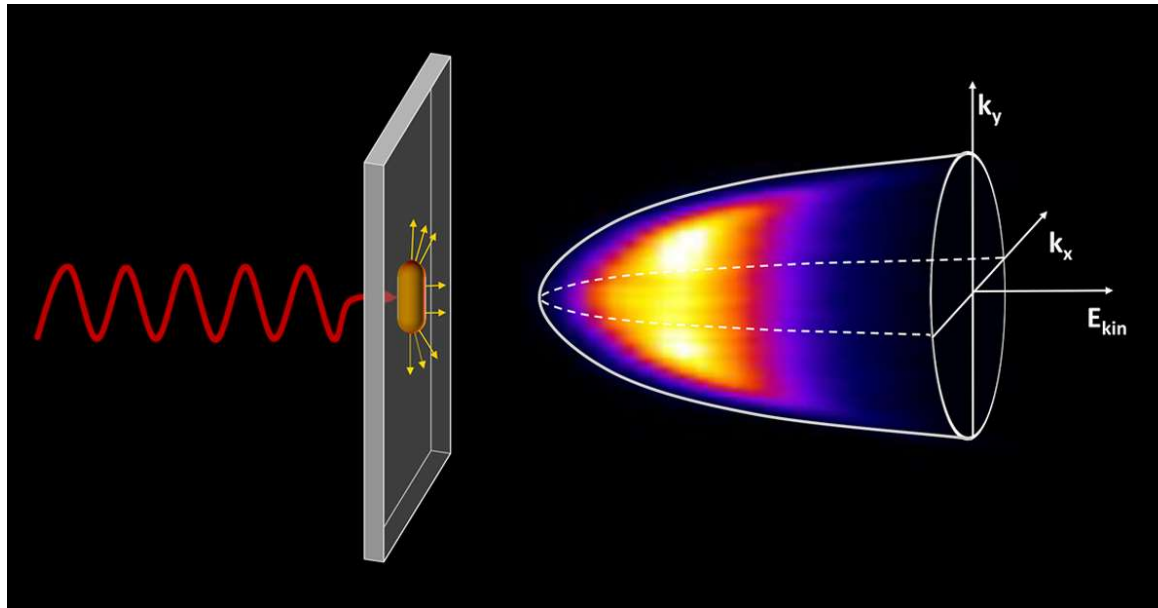
$$\vec{m} = \left(\frac{4\pi}{3} R^3 \right) 3\epsilon_0\epsilon_m \frac{\epsilon - \epsilon_m}{\epsilon + 2\epsilon_m} \vec{E}_0$$

$$\vec{E}(\vec{r}) = \vec{E}_0 + \vec{E}_{\text{pol}}(\vec{r}) \quad \vec{E}_{\text{pol}}^{(\text{int})} = \frac{\epsilon_m - \epsilon}{\epsilon + 2\epsilon_m} \vec{E}_0$$

polarisabilité de la nanoparticule $\alpha(\omega)$



Distribution de moments des électrons chauds à l'échelle de l'objet individuel - PEEM Espace réciproque



Montage Exp.

Bâtonnet Au 67 ± 2 nm x 19 ± 2 nm,

Substrat ITO / SiO₂

Résonance plasmon

$\lambda_{\text{Res}} = 795$ nm, FWHM = 41 nm, 80 meV

Illumination suivant la normale arrière

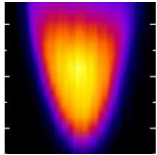
Champ électrique $E_0 // k_x$

- Microscopie PEEM à détection Temps de Vol dans l'espace réciproque
- Mesure de la densité d'états $\rho(k_x, k_y, E_{\text{cin}})$
- Détermination de la distribution des moments des électrons photoémis d'un bâtonnet Au à résonance plasmon

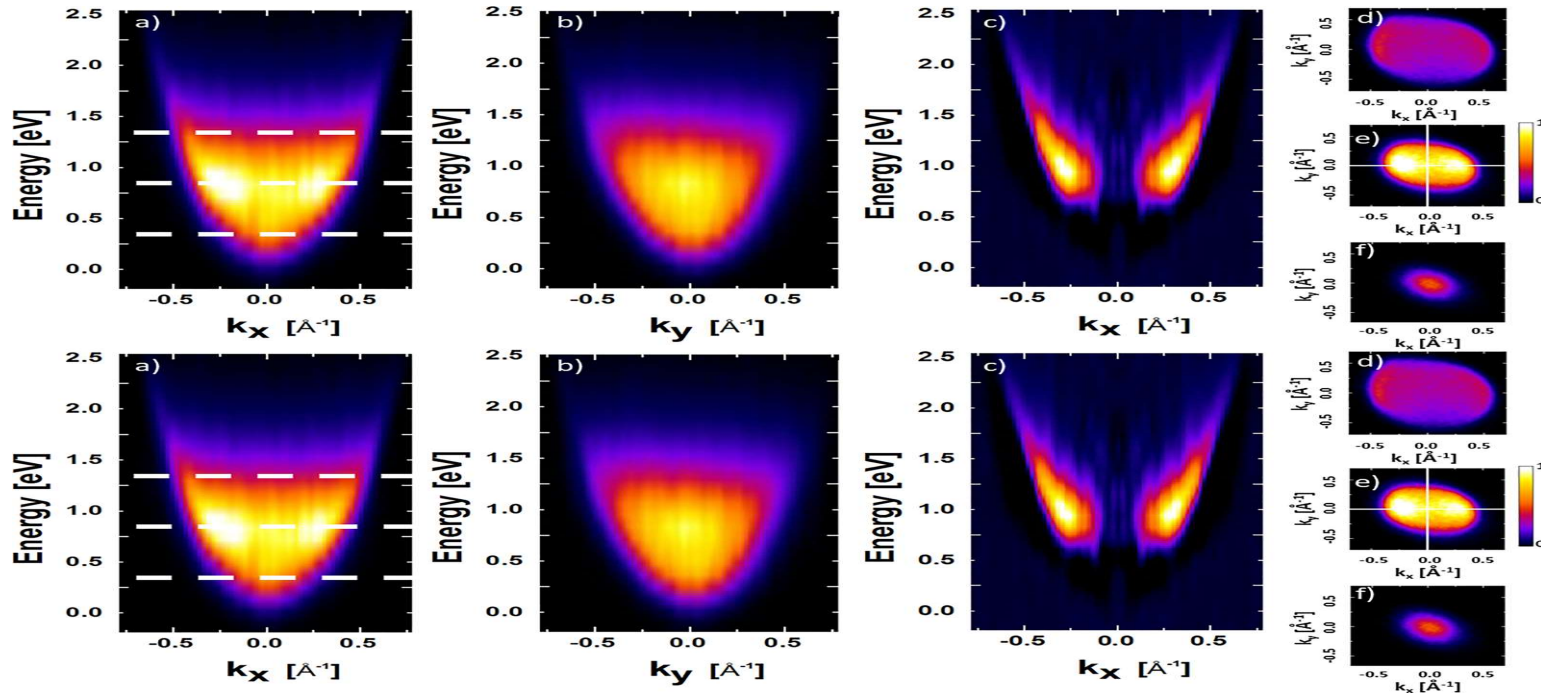
Momentum Distribution of Electrons Emitted from Resonantly Excited Individual Gold Nanorods

M. Lehr, B. Foerster, M. Schmitt, K. Krüger, C. Sönnichsen, G. Schönhense, H.-J. Elmers

Nano Lett. **17** (2017) 6606 DOI: 10.1021/acs.nanolett.7b02434



Distribution de moments des électrons chauds à l'échelle de l'objet individuel – PEEM Espace réciproque

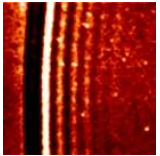


Bâtonnet Au individuel (a, b) Profils des moments suivant les directions k_x et k_y ; (c) Soustraction des profils (a) et (b); (d-f) coupes transverses aux énergies cinétiques 1.3, 0.8 et 0.3 eV, cf. (a). Polarisation du champ électrique suivant la direction k_x .

➤ Deux composantes de moment distinctes :

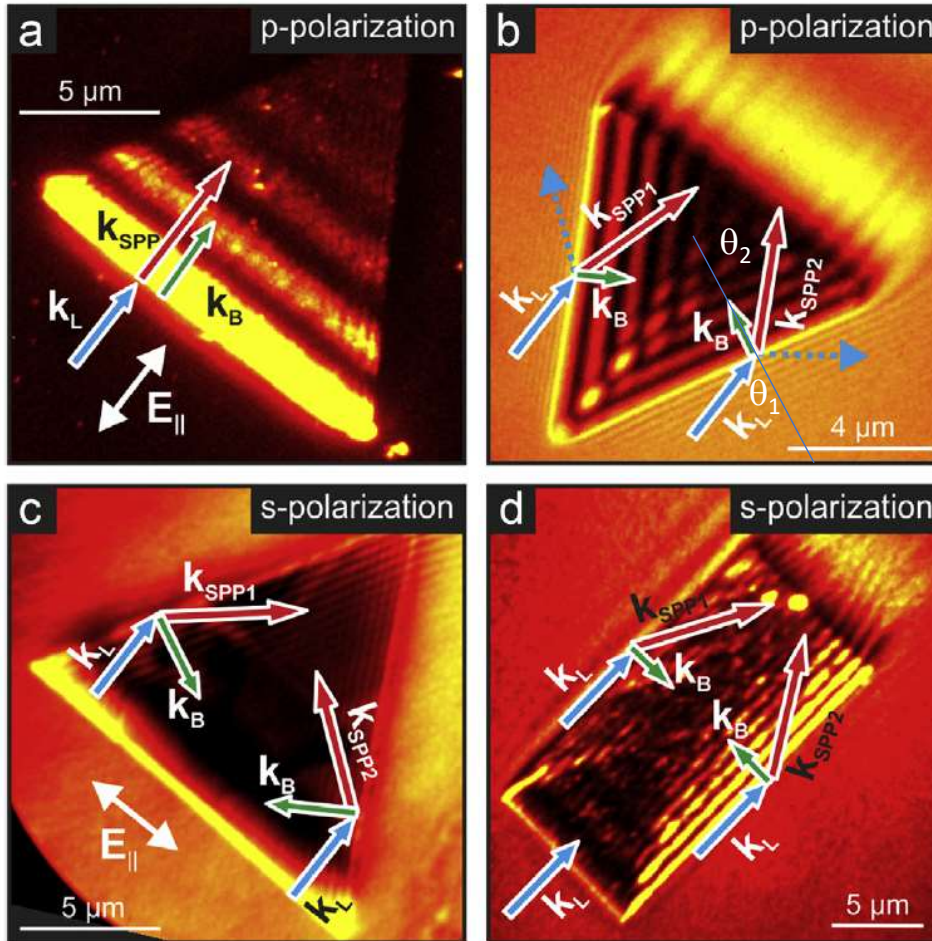
(i) Une **composante isotrope** liée à la photoémission non linéaire à partir du gaz d'électrons chauds (> 90 %, diffusion multiple),

(ii) Une **composante anisotrope** liée à l'émission de champ (effet tunnel sous champ optique) aux extrémités du bâtonnet suivant l'axe longitudinal (< 10 %). Facteur de Keldysh $\sim 1 - 3$. Régime de transition $n.h\nu$ vs Fowler-Nordheim



Propagation of plasmons-polaritons (nm, fs) – PEEM

Symétrie 2D – Loi Snell-Descartes - Interface Ag / vide



➤ Loi de Snell-Descartes

- .Triangle Ag / Si(111)
- .PEEM 2 photons

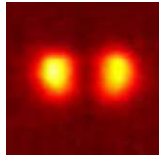
- ➡ Onde incidente $k_{//}$, milieu n_{vide}
- ➡ Onde SPP k_{SPP} , milieu n_{Ag}
- ➡ Figure de battements k_B (Moiré)

$$\vec{k}_B = \vec{k}_{\text{SPP}} - \vec{k}_{//}$$

$$k_{//} \cdot \sin(\theta_1) = k_{\text{SPP}} \cdot \sin(\theta_2)$$

➤ Validation de la loi Snell-Descartes pour la réfraction

- Onde libre → Onde plasmon - polariton
- Onde plasmon - polariton → Onde libre



Cathodoluminescence, a tool for plasmonics

Basic principle – CL probability vs EMLDOS

In quasi-static approximation

$$\Gamma_{CL}^{sphere}(\omega, \vec{R}_{\perp}) = \frac{e^2}{\pi \hbar \omega^2} \sum_i \Im(f_i(\omega)) \left| TF_z(\vec{E}_i^z(\vec{R}_{\perp}, \frac{\omega}{v})) \right|^2$$

f_i generalized polarizability, i.e. the spectral dependence variation (plasmon energies = f_i poles)
 TF_z is a Fourier transform along the e-beam direction at point $\vec{R}_{\perp} = (x, y)$ in real space and momentum $q_z = \omega / v$ in reciprocal space

- For bright modes and within a TF_z , CL maps spectrally and spatially the zEMLDOS, i.e. the electromagnetic density of states in the direction along the e-beam axis
- CL = Out-of-plane EMLDOS for bright modes
- Electron selection rules \neq photon selection rules \rightarrow Dark modes accessible
- Direct control over output polarization is possible

➤ The electric field parallel to the electron beam is described by a temporal Gaussian wavepacket where Δp is the light pulse duration and τ is the delay between the arrivals of the photon and the electron pulses at the position of the sample.

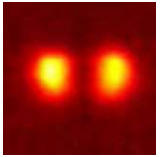
$$E_z(z, t) = E_z(z) \exp\left[-i\omega t - \frac{(t + \tau)^2}{\Delta_p^2}\right]$$

➤ EELS, EEGS, CL probabilities densities for the dipole plasmon of a sphere within the quasi static approximation

$$\Gamma_{EELS}^{sphere}(\omega, R_{\perp}) \propto \left(\frac{\omega}{\gamma v^2}\right)^2 \left(K_1^2\left(\frac{\omega R_{\perp}}{\gamma v}\right) + \frac{1}{\gamma^2} K_0^2\left(\frac{\omega R_{\perp}}{\gamma v}\right) \right) \Im(\alpha_{l=1}(\omega))$$

$$\Gamma_{EEGS}^{sphere}(\omega, R_{\perp}) \propto \left(\frac{\omega}{\gamma v^2}\right)^2 I_0 K_1^2\left(\frac{\omega R_{\perp}}{\gamma v}\right) |\alpha_{l=1}(\omega)|^2 \delta(\omega - \omega_i)$$

$$\Gamma_{CL}^{sphere}(\omega, R_{\perp}) \propto \omega^3 \left(\frac{\omega}{\gamma v^2}\right)^2 \left(K_1^2\left(\frac{\omega R_{\perp}}{\gamma v}\right) + \frac{1}{\gamma^2} K_0^2\left(\frac{\omega R_{\perp}}{\gamma v}\right) \right) |\alpha_{l=1}(\omega)|^2$$



Cathodoluminescence, a tool for plasmonics

Basic principle – Coherent CL probability

- The transient electric field associated to the e-beam is similar to a plane wave pulse of white light. The NP sees a EM pulse containing a large spectrum of frequencies.
- In the quasi-static approximation, the exciting field is static, i.e. presents no spatial variation over the particle size. Thus, it couples only to the $l=1$ dipolar mode.

$$\Gamma_{CL}^{sphere}(R_{\perp}, \omega) \propto a^6 |\alpha_{l=1}(\omega)|^2 (K_1^2(\omega R_{\perp}/v) + K_0^2(\omega R_{\perp}/v))$$

$$\Gamma_{CL}^{sphere}(\omega, R_{\perp}) \propto a^6 |\alpha_{l=1}(\omega)|^2 \cdot \exp\left(-\frac{R_{\perp}}{v_e/\omega}\right)$$

a Sphere diameter; $R_{\perp} = (x, y)$ Impact parameter of the electrons traveling along the z direction at speed v_e ; $\hbar\omega$ Energy of the emitted photon; K_m Modified Bessel function of the second kind; α_l Sphere polarizability for mode l

- Formally, the CL probability of a small sphere is proportional to its scattering cross section as measured in far field optics, $\sigma_{sca.} \propto a^6 |\alpha_{l=1}(\omega)|^2$
- CL probability is position-dependent with a quasi-exponential decay with e-beam to sphere distance R_{\perp} , attenuation length $v_e/\omega \sim 10$ nm
- Electron selection rules \neq photon selection rules \rightarrow Dark modes accessible



What is plasmonics ?

➤ “A way to confine electromagnetic fields over dimensions on the order or smaller than the wavelength λ_{hv} ”

S. Maier in Plasmonics: Fundamentals and Applications (2007) Springer

➤ Interaction processes between electromagnetic radiation and conduction electrons at metallic interfaces = **coherent collective charge oscillations**

➤ **Basic ingredients**

(i) *Surface plasmons-polaritons* SPP - Metal / dielectric interface - Hybrid wave between a photon and a plasma oscillation - Propagative mode along the interface, evanescent in perpendicular direction

(ii) *Localised surface plasmons* LSP - Sub wavelength object - Non propagative mode



The promise of Plasmonics

- A way to bridge the size gap between nanoelectronics and photonics

	Working frequency	Spatial scale
Photonics	High working frequency Optical frequency 500 THz (600 nm) = $5 \cdot 10^{14}$ Hz 500 THz = 500 000 GHz	Low spatial integration $\sim \lambda_{hv}$ Light wavelength ~ 600 nm in visible spectrum
Plasmonics	High working frequency Optical frequency 500 THz (600 nm) = $5 \cdot 10^{14}$ Hz 500 THz = 500 000 GHz	Moderate - High spatial integration $\lambda_{hv} / 10 \sim 60$ nm (visible)
Electronics	Low working frequency ~ 1 GHz = $1 \cdot 10^9$ Hz	High spatial integration Int. Tech. Roadmap for Semicond. → MOSFET scaling 5 nm in 2020



Plasmonic near field – Experimental relevant scales

- Investigation of the full plasmonic picture requires adequate experimental resolutions in

.space

.time

.energy

- Additional degrees of freedom are

.light polarisation

.light angular momentum

.electron momentum distribution



Plasmonics - Physical orders of magnitude - Spatial scale

Relevant length scales of a plasmonic field

- Near field phenomena imply field spatial distribution scale \ll Light wavelength λ_0
- Localized surface plasmon
 - Collective coherent electron oscillation
 - Electrons perceive a static electric field amplitude (quasi static QS approximation)
 - Object dimension $L \ll$ Light wavelength λ_0
- Thomas Fermi screening length ≈ 0.1 nm \ll Coherent charge fluctuation period
- Propagation length of a surface plasmon polariton $L_{prop.} = 1/e$ plasmonic field decay length

$$L_{prop} = \frac{1}{k_x''} \quad k_x'' = \text{Im} \left\{ \frac{\omega}{c} \sqrt{\frac{\epsilon_{Dielec} \epsilon_{Metal}}{\epsilon_{Dielec} + \epsilon_{Metal}}} \right\}$$

N.A. Au/vacuum interface @ 800 nm wavelength excitation $L_{prop.} = 88 \mu\text{m}$

A few tenths of a nanometer ~ 0.1 nm = 1×10^{-10} m

<

Plasmonic Spatial scale

<

A few tens of micrometers $\sim 10 \mu\text{m} = 1 \cdot 10^{-5}$ m



Plasmonics – Physical orders of magnitude – Time scale

Dynamics of the plasmonic near field

➤ Characteristic times of plasmonic physics

.Photon absorption time = Half-period of a Rabi oscillation $\sim 1 \cdot 10^{-16} \text{ s} = 100 \text{ as}$

.Photon field oscillation $\sim 1 / 500 \text{ THz} \approx 1 \cdot 10^{-15} \text{ s} = 1 \text{ fs}$

.Plasmonic field oscillation $\sim 1 / 500 \text{ THz} \approx 1 \cdot 10^{-15} \text{ s} = 1 \text{ fs}$

.Plasmon coherence lifetime $\sim 1 \cdot 10^{-14} \text{ s} = 10 \text{ fs}$

.Thermalisation time of a hot e^- gas $\sim 1 \cdot 10^{-13} \text{ s} = 100 \text{ fs}$

.Thermalisation time of a hot e^- gas coupled to a phonon bath $\sim 1 \cdot 10^{-12} \text{ s} = 1 \text{ ps}$

A few tenths of a femtosecond $\sim 0.1 \text{ fs} = 1 \times 10^{-16} \text{ s}$

<

Plasmonic Time scale

<

One picosecond $1 \text{ ps} = 1 \cdot 10^{-12} \text{ s}$



Plasmonics – Physical orders of magnitude – Energy scale

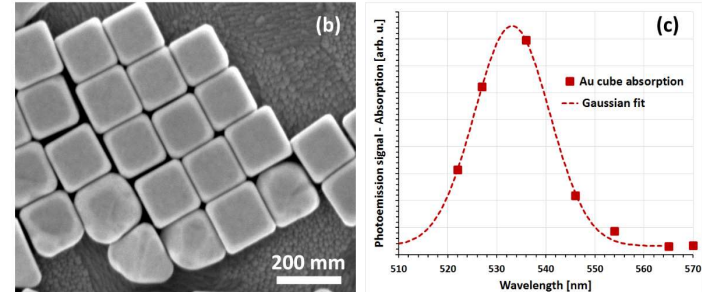
Energy of a localised surface plasmon, surface plasmon polariton

- Localised plasmon resonance energy - Full Width at Half Maximum FWHM

$$\text{FWHM} = \frac{2\hbar}{\text{Plasmon coherence time } T}$$

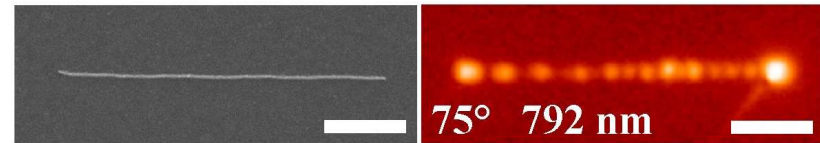
N.A. Plasmon coherence time $T \approx 10 \text{ fs} = 1 \cdot 10^{-14} \text{ s}$

FWHM $\approx 100 \text{ meV} \Leftrightarrow 23 \text{ nm}@530 \text{ nm}$



- Energy of a plasmon propagating along an infinite cylinder of sectional radius R

$$\lambda_{SR-SPP} = 2\pi R \left(a_1 + a_2 \frac{\lambda_0}{\lambda_{Au \text{ plasma}}} \right)$$



N.A. $R = 20 \text{ nm}$, $\lambda_{0 \text{ vacuum}} = 792 \text{ nm}$, $\lambda_{Au \text{ plasma}} = 138 \text{ nm}$, $(a_1, a_2) = f(\epsilon_{Au})$

$\lambda_{SR-SPP} = 335 \text{ nm} \Leftrightarrow E_{SR-SPP} = 3.7 \text{ eV}$, so in the range 1 – 10 eV

A few tens of meV ~ 10 meV = 0.01 eV

<

Plasmonic Energy scale

<

Several eV ~ 10 eV



Plasmonic near fields – Physical orders of magnitude

A few tenths of a nanometer $\sim 0.1 \text{ nm} = 1 \times 10^{-10} \text{ m}$

<

Plasmonic Spatial Scale

<

A few tens of micrometers $\sim 10 \text{ }\mu\text{m} = 1 \cdot 10^{-5} \text{ m}$

A few tenths of a femtosecond $\sim 0.1 \text{ fs} = 1 \times 10^{-16} \text{ s}$

<

Plasmonic Time Scale

<

One picosecond $1 \text{ ps} = 1 \cdot 10^{-12} \text{ s}$

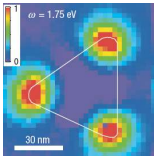
A few tens of meV $\sim 10 \text{ meV} = 0.01 \text{ eV}$

<

Plasmonic Energy Scale

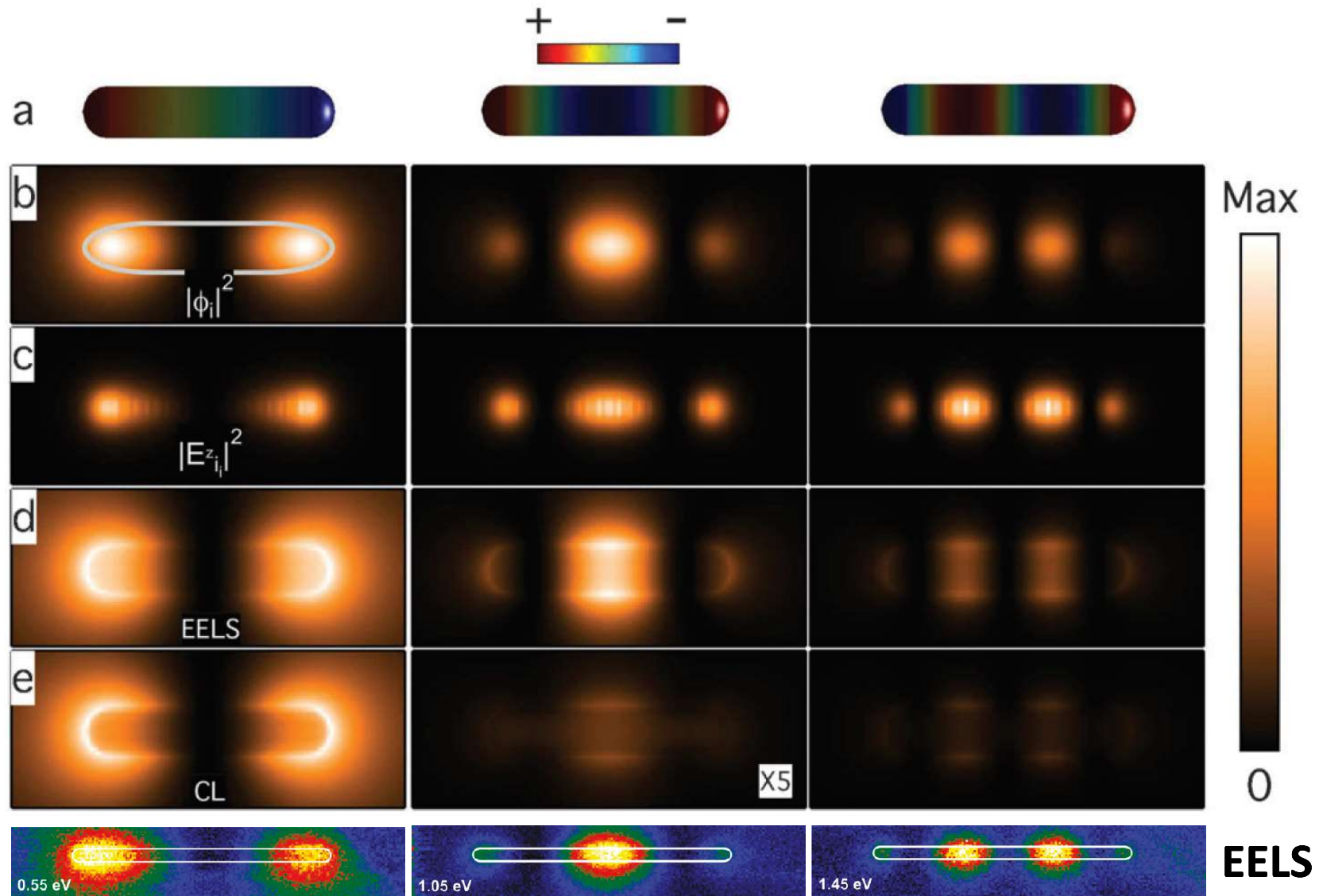
<

Several eV $\sim 10 \text{ eV}$



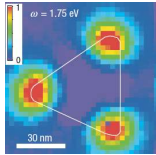
Electron energy loss spectrometry, a tool for plasmonics

Basic principle – EELS probability



D. Rossouw *et al.* *Nano Lett.* **11** (2011) 1499

M. Kociak & O. Stéphan *Chem. Soc. Rev.* **43** (2014) 3865



Electron Energy loss spectrometry, a tool for plasmonics

Basic principle – EELS probability for a small sphere

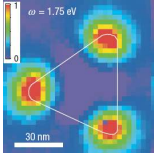
- The electron electric field is similar to a plane wave pulse of white light. The NP sees a pulse containing a large spectrum of frequencies
- In the quasi-static QS approximation, the exciting field is static, i.e. presents no spatial variation over the particle. Thus, it couples only to the $l = 1$ dipolar mode. For non relativistic electrons, we obtain:

$$\Gamma_{\text{EELS}}^{\text{sphere}}(\omega, R_{\perp}) \propto a^3 \Im(\alpha_{l=1}(\omega)) (K_1^2(\omega R_{\perp}/v) + K_0^2(\omega R_{\perp}/v))$$

$$\Gamma_{\text{EELS}}^{\text{sphere}}(\omega, R_{\perp}) \propto a^3 \Im(\alpha_{l=1}(\omega)) \cdot \exp\left(-\frac{R_{\perp}}{v/\omega}\right)$$

$$\sigma_{\text{ext.}} \propto a^3 \Im(\alpha_{l=1}(\omega))$$

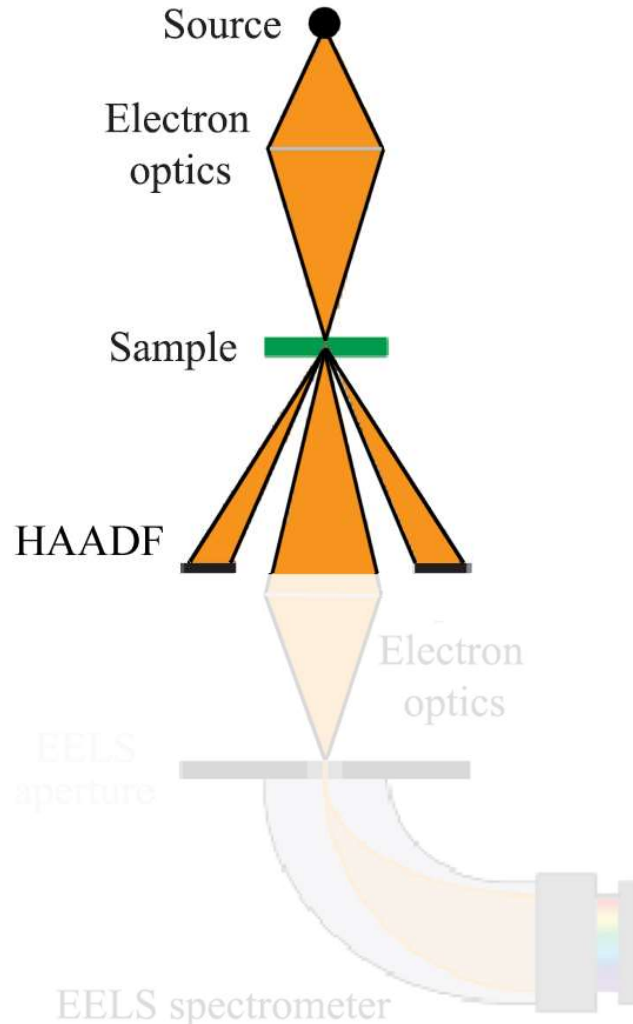
- Formally, the EELS probability of a small sphere is proportional to its absorption cross-section as measured in far field optics
- EELS probability is position-dependent with a quasi-exponential decay with e-beam to sphere distance R_{\perp} , attenuation length = $v/\omega \sim 10$ nm



Electron energy loss spectrometry, a tool for plasmonics

Instrumentation – STEM Bright Field Imaging mode

STEM - EELS



➤ Electron imaging

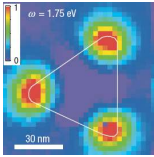
Electron source (electron field gun)

Electron optics

The electron beam is focused and raster scanned on the sample. Beam diameter $\varnothing \leq 1 \text{ nm}$

➤ **SEM Imaging.** Image is built on backscattered, secondary and/or Auger electrons

➤ **TEM Imaging.** Image is built on transmitted electrons

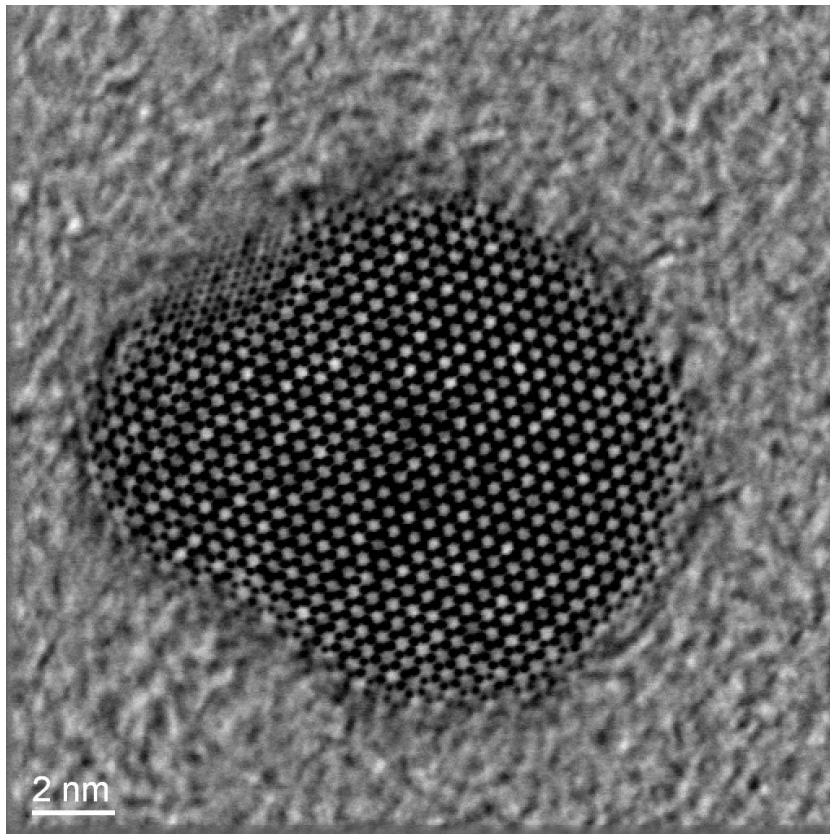


Electron energy loss spectrometry, a tool for plasmonics

Instrumentation – STEM Imaging mode

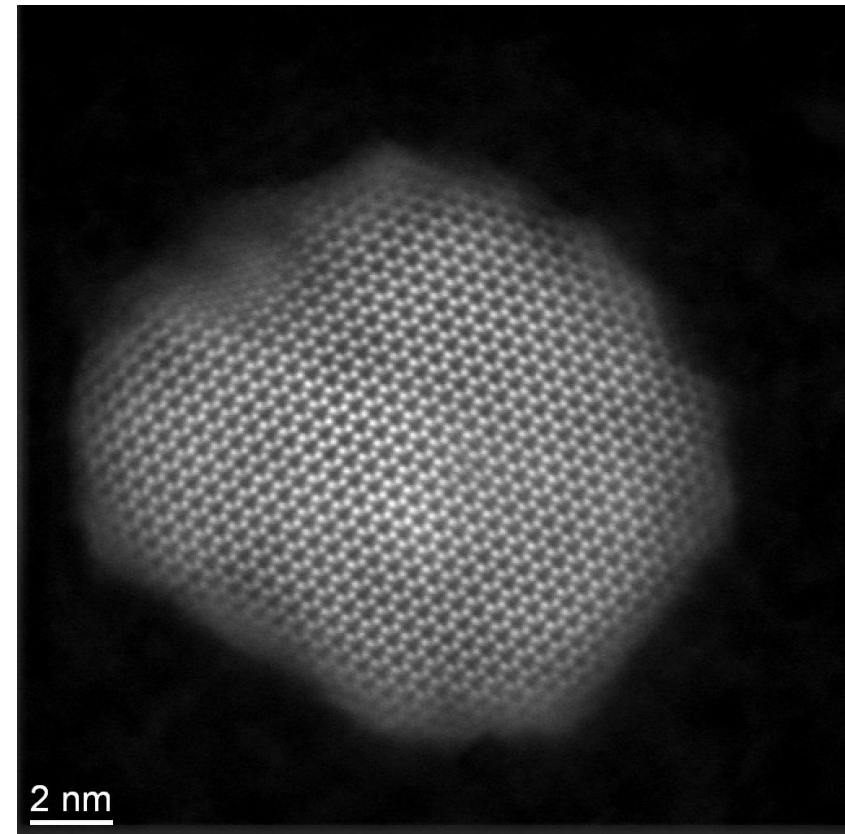
Bright field imaging mode

CdSe Platelets, courtesy B. Dubertret

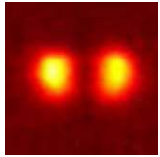


Dark Field imaging mode

CdSe Platelets, courtesy B. Dubertret

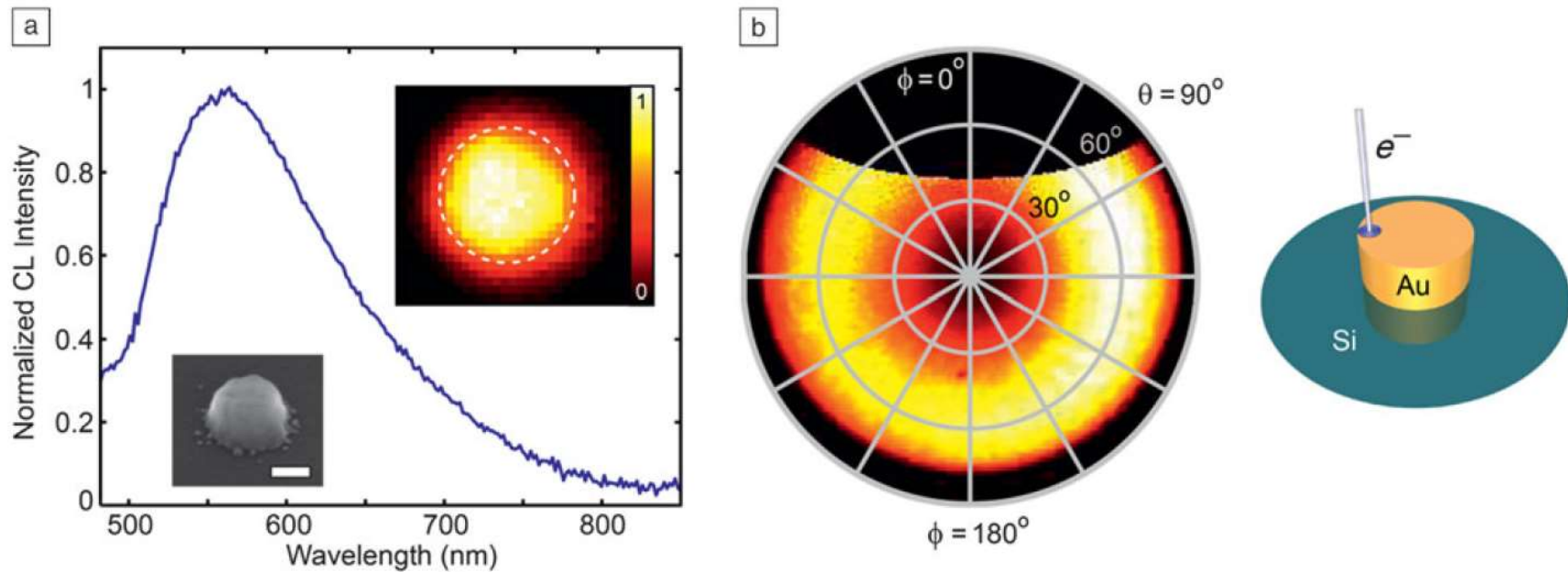


- Fast electron probes can be made much smaller than the typical visible light wavelength. Atomic resolution ≈ 0.1 nm possible



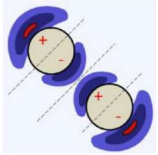
Cathodoluminescence, a tool for plasmonics

Cathodoluminescence near field spectro. – STEM CL (λ) mode



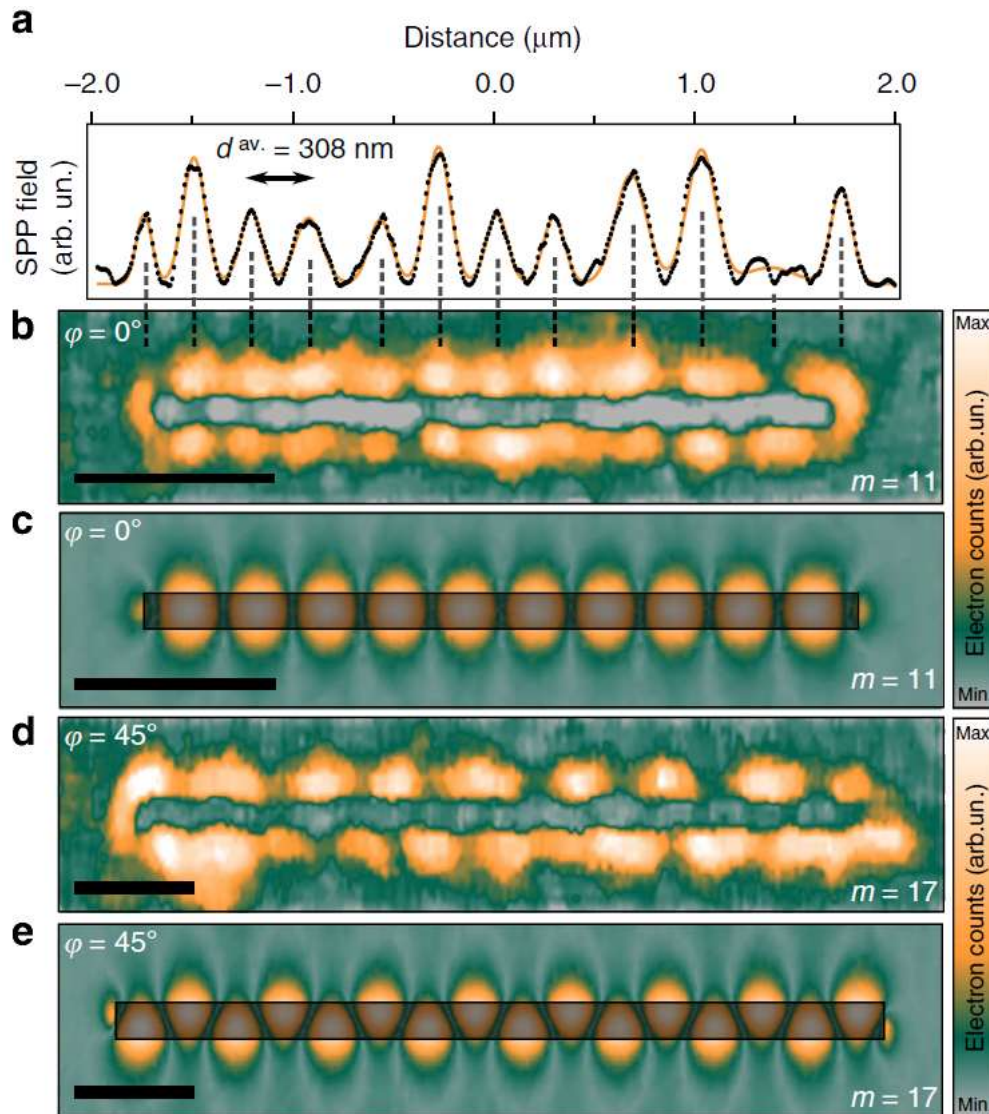
Au nanoparticle 100 nm in diameter and 80 nm in height on Si

- CL Spectrometry. (a) CL spectrum spatially averaged over the particle with a 5 nm resolution. A clear resonant spectrum is observed, which reflects the CL radiation of a vertically-oriented dipolar plasmon resonance in the Au NP peaking at $\lambda = 560$ nm
- Angle resolved CL imaging. (b) Angular distribution of the CL radiation emitted by the Au NP. Off center e^- beam excitation translates into an asymmetric intensity profile (\perp & $//$ dipoles)

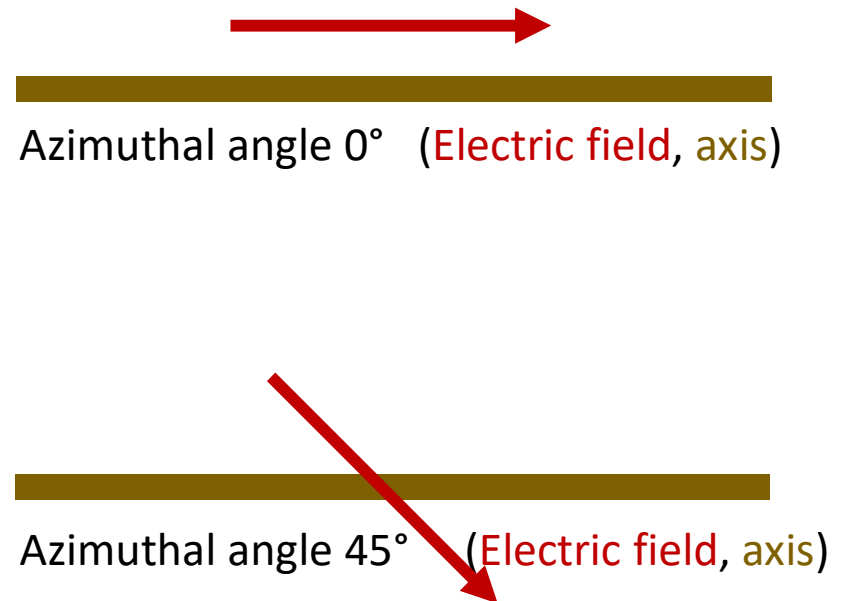


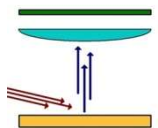
PINEM Near field imaging

Plasmonics of 1D objects - Nanowires, polarization dependence



Ag Nanowire 3.4 μm in length, 90 nm in diameter. **800 nm excitation wavelength**. EEG electrons at time delay $\Delta t = 0 \text{ ps}$. Scale bar 1 μm .



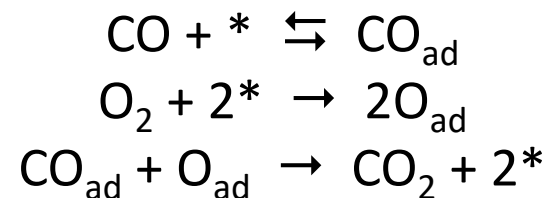


PEEM – photoemission electron microscopy (1933)

Oxidation of carbon monoxide on Pt(110)



- Oxidation reaction ($445 \times 445 \mu\text{m}^2$)



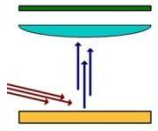
* = Free Pt(110) site

Carbon monoxide “Bright” $\Phi = 5.8 \text{ eV}$

Oxygen “Dark” $\Phi = 6.5 \text{ eV}$

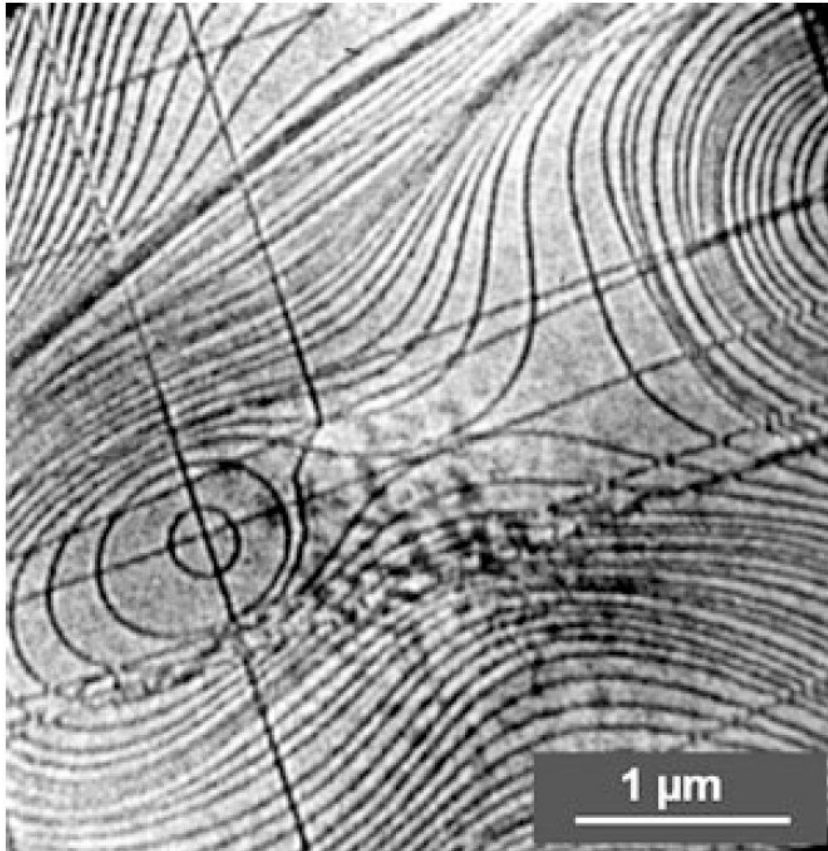
Freedom degrees $P_{\text{CO}} = 4.3 \cdot 10^{-5} \text{ mb}$, $P_{\text{O}_2} = 4 \cdot 10^{-4} \text{ mb}$, $T = 448 \text{ K}$

- Spatio-temporel pattern of the surface reaction (spiral diffusion fronts)

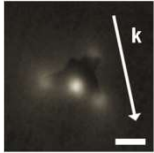


LEEM – low energy electron microscopy (1962)

Mo(100) Surface

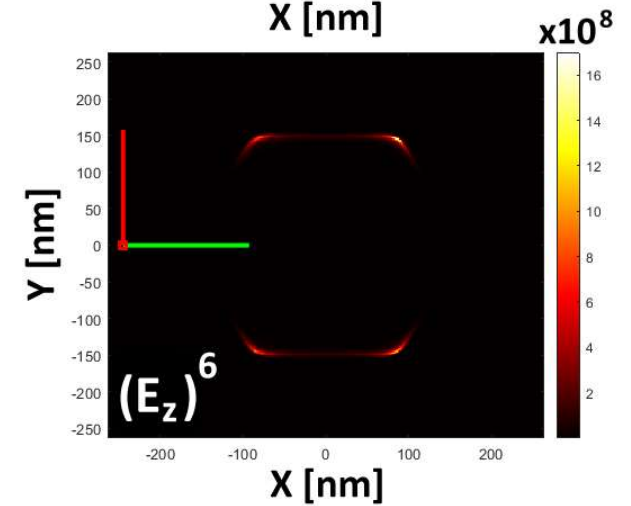
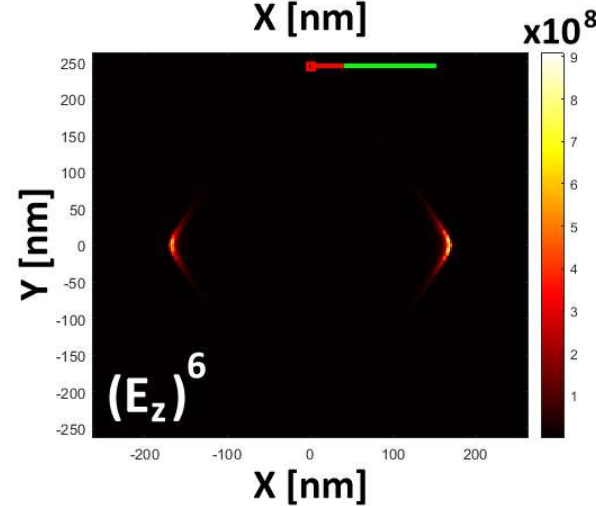
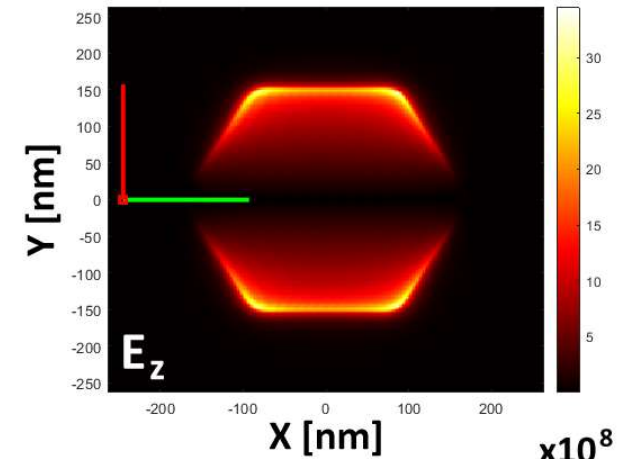
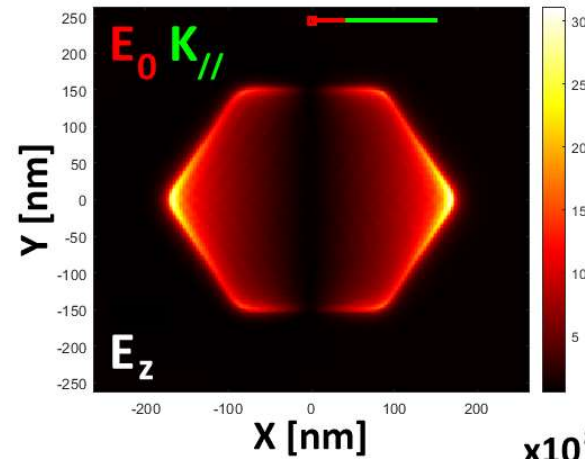
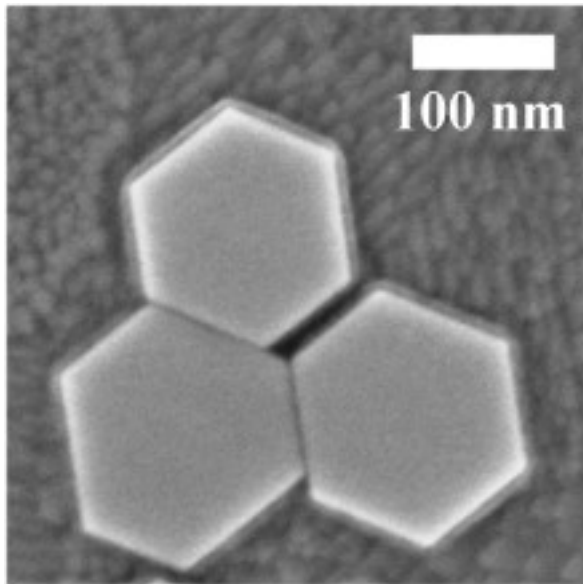


- Mo(110) Surface
LEEM
Electron kinetic energy 14 eV
Monoatomic step contrast



Plasmonics of 2D objects - Nanohexagon D_{6h} - PEEM

Near field mapping - Linear polarisation



Au Hexagon - SEM

$L = 150 - 200 \text{ nm}$

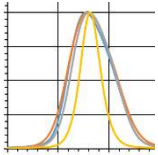
Thickness $\approx 15 \text{ nm}$

(Colloidal synthesis, CEA S. Marguet)

➤ *Boundary Element Method (BEM) Simulation*

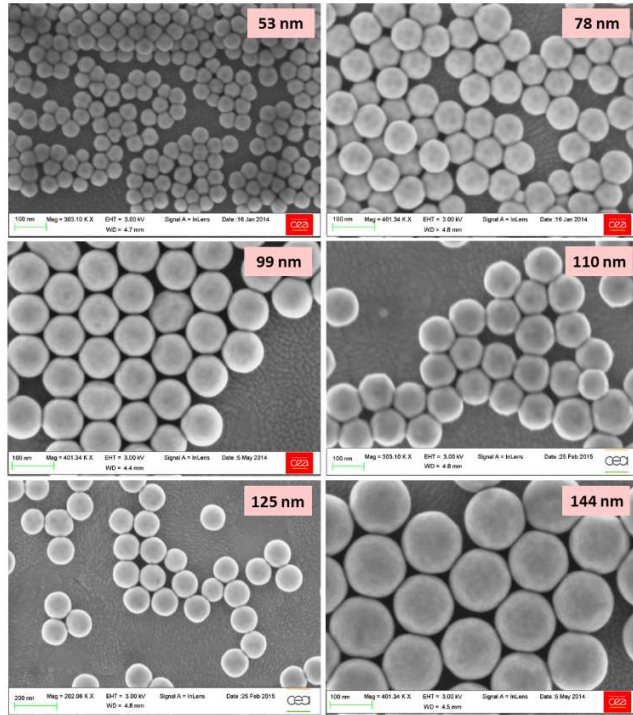
Au Hexagon

Electric field maps, z components $|E_z|$ & $|E_z|^6 = 2 \times 3$



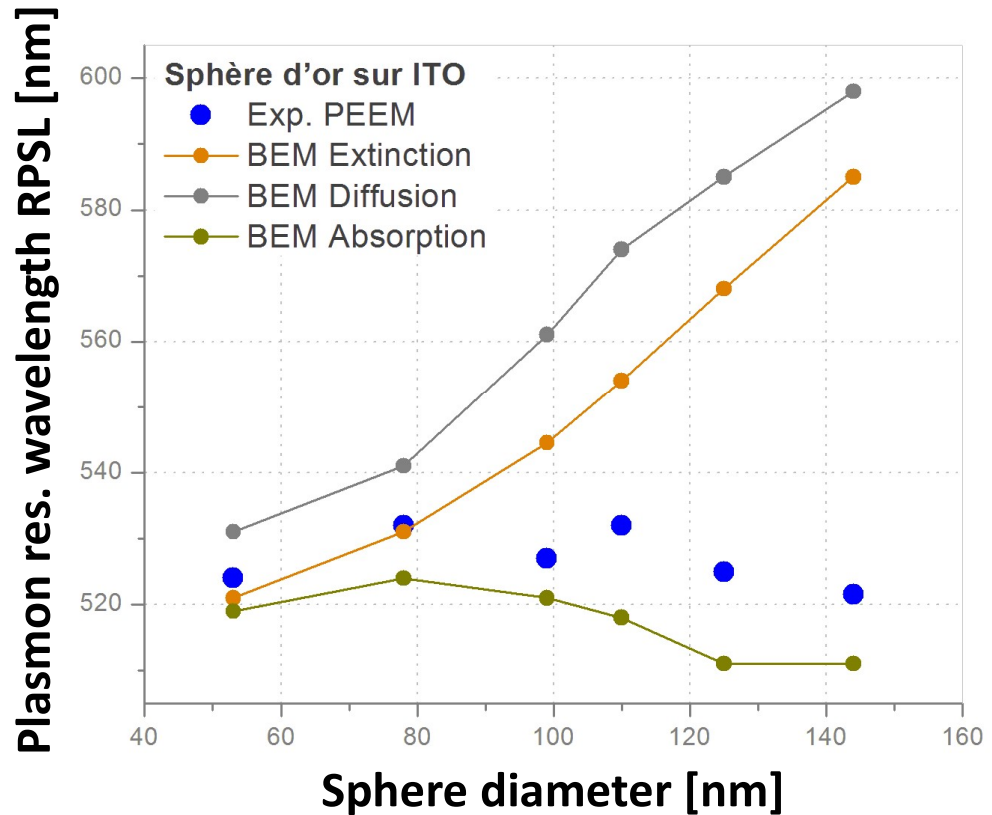
Non linear photoemission - PEEM – Absorption spectrum

Spheres - Absorption resonance = $f(\text{diameter } 2R)$

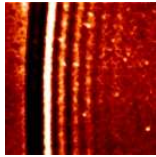


Au colloïdal spheres

(S. Marguet CEA, NIMBE)

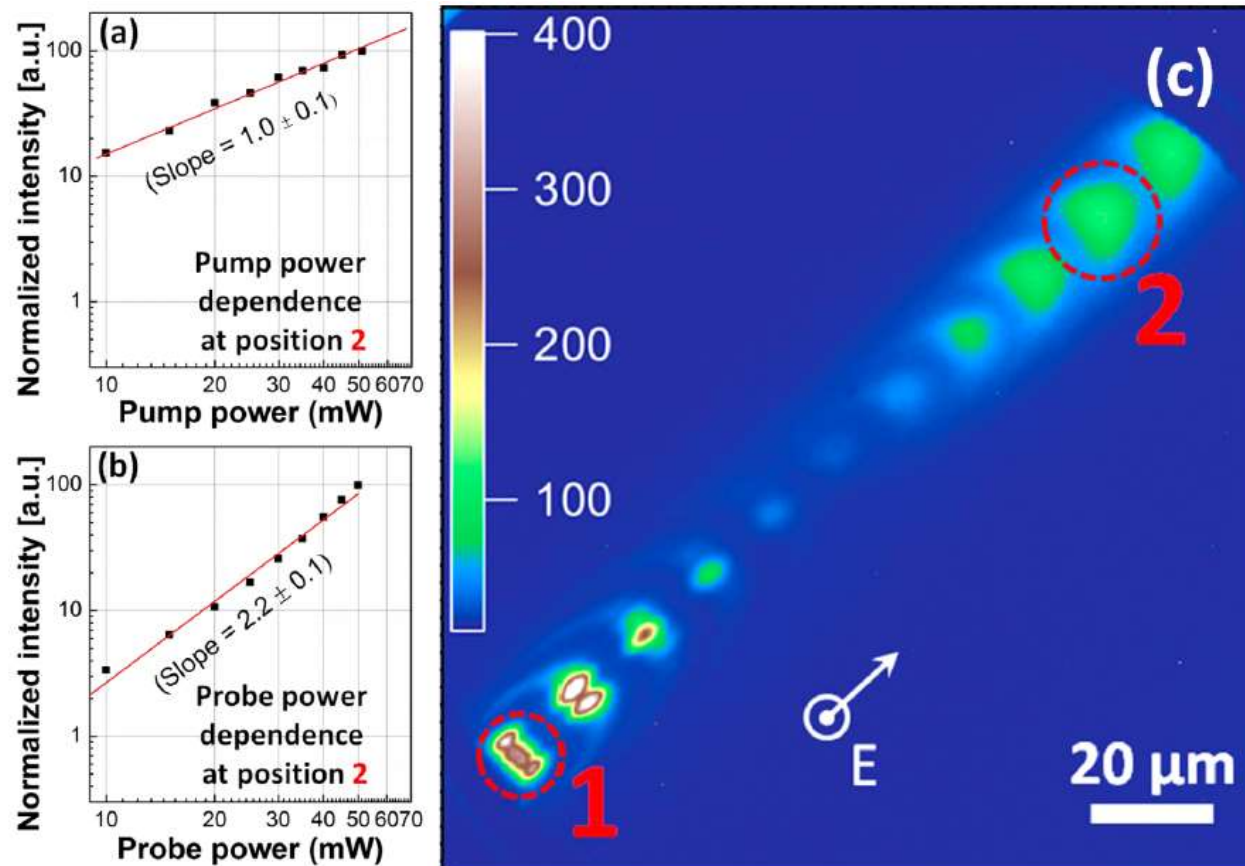


- Plasmon resonance maxima vs sphere diameter $2R$
- Absorption spectrum on individual object, $I_{\text{photoemission}} = f(\text{incident wavelength})$
- Spectral resolution $\approx 1 \text{ nm}$ (130 fs, 2.5 meV)

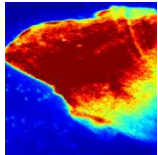


Propagation of plasmons-polaritons (nm, fs) – PEEM

2D Symmetry – Pump-probe experiment - Au / vide interface

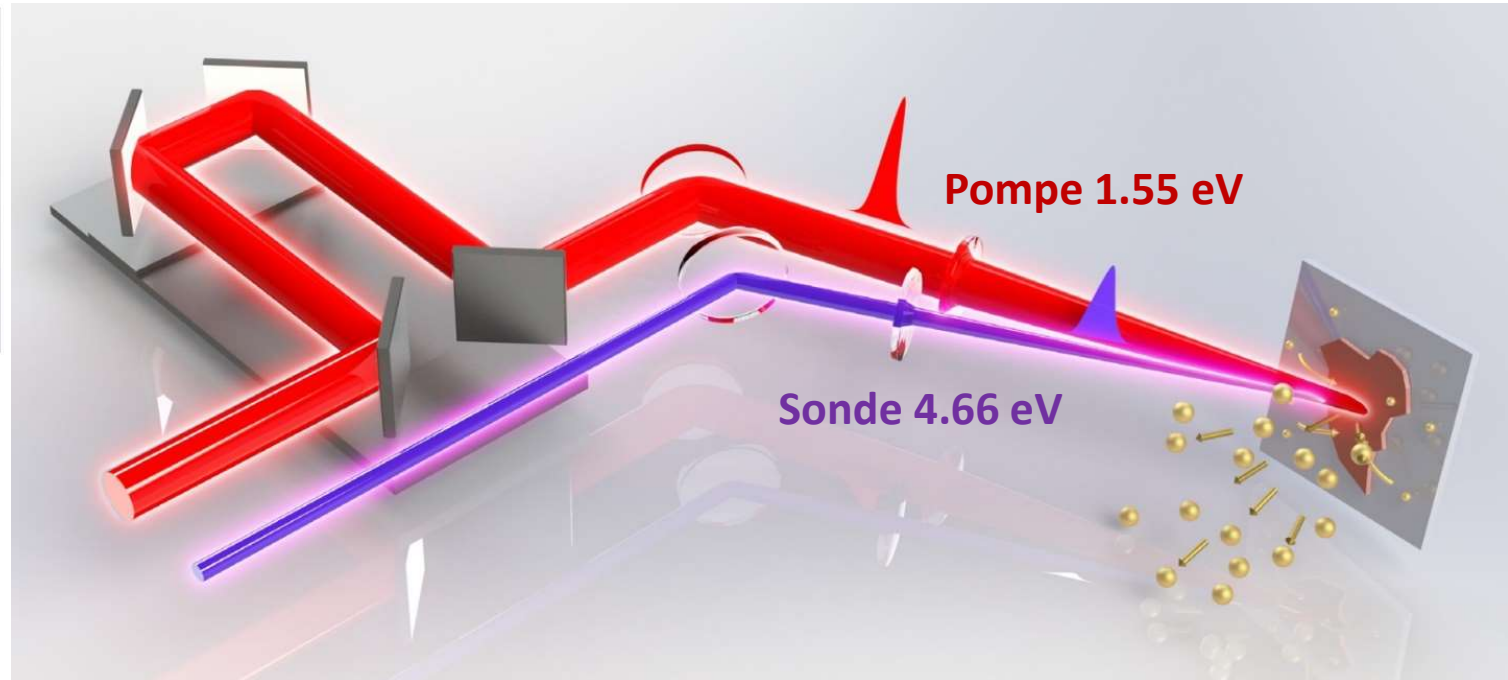
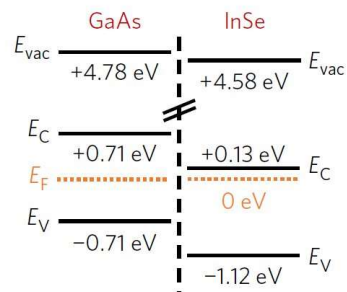
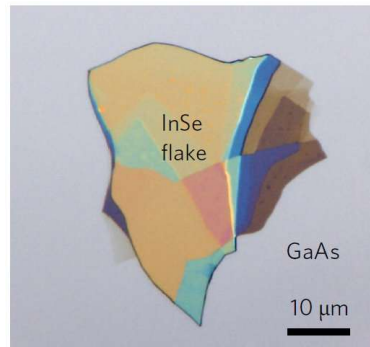


- **PEEM Region 1.** SPP signal close to the geometric launcher $I_{\text{PEEM}} \propto (E_{\text{pump}})^6$
 - **PEEM Region 2.** SPP signal far away from the launcher $I_{\text{PEEM}} \propto (E_{\text{pump}})^2 \cdot (E_{\text{probe}})^4$
- Sequential coherent photoemission process. Attenuation $\delta(\text{Au}, 800 \text{ nm}) = 88 \mu\text{m}$



Electron dynamics in a solid - PEEM

Time-resolved PEEM variant – (space, time, energy) = (nm, fs, eV)



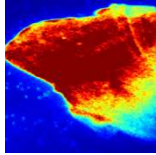
- Investigation of the electron dynamics (space, time, energy) in an elementary (p, n) junction (InSe, AsGa) = InSe flake on a AsGa substrate

Two colors Pump Probe experiment:

pump laser NIR 800 nm 1.55 eV

probe laser UV 266 nm 4.66 eV

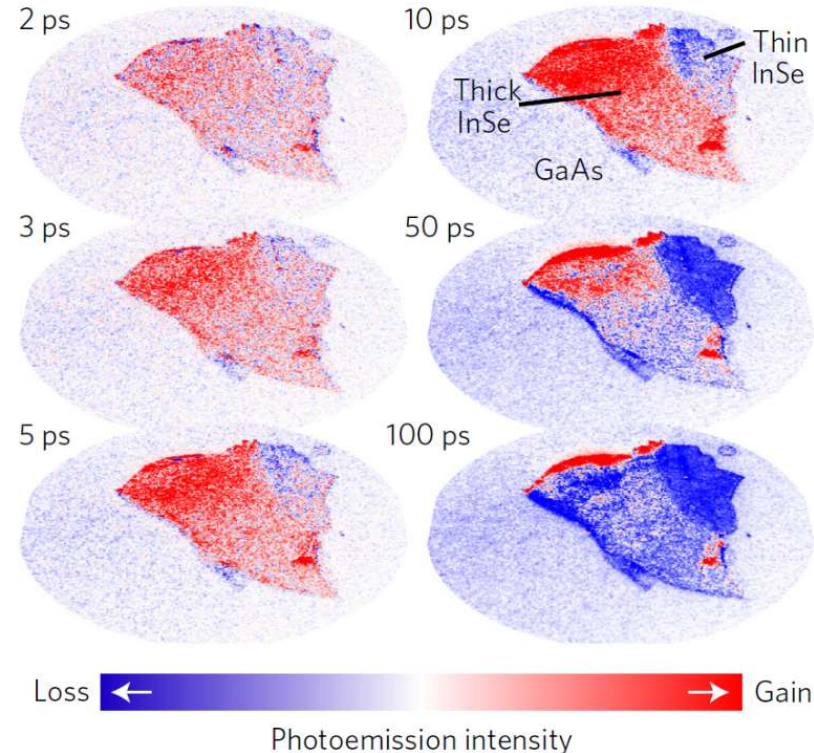
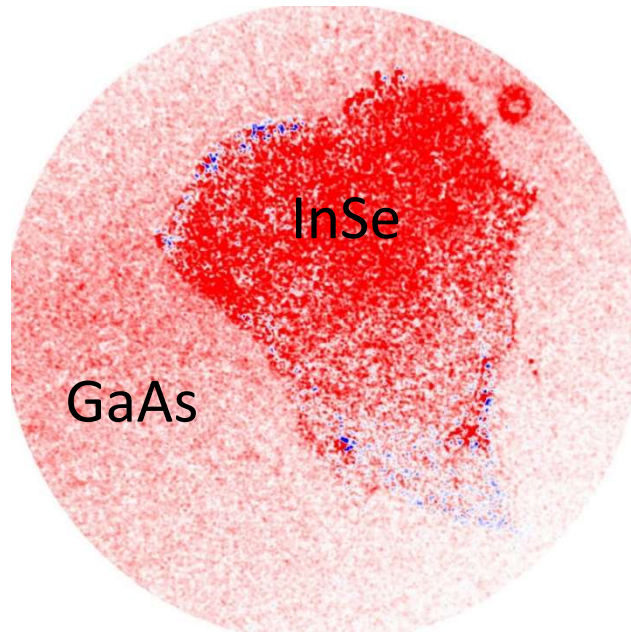
LEEM - PEEM III Microscope



Electron dynamics in a solid - PEEM

Time-resolved PEEM variant – (space, time, energy) = (nm, fs, eV)

0 ps



➤ PEEM Image in energy-integrated mode @ $\Delta t = 0$ ps

Non-equilibrium distribution of charges with high-energy electrons localized in GaAs and in available states in InSe due to a lower conduction band minimum

Electron temperature ≈ 1700 K

➤ Electron transport over time in 2 steps

(i) e^- accumulate in all parts of InSe at early time delays due to electron transfer from high-energy GaAs states

(ii) the initial rapid accumulation of charge in various parts of InSe slows down (electric field), followed by eventual recombinations

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Vitesse d'un electron relativiste

$$v^2 = c^2 \cdot (1 - 1 / (1 + E / m_e c^2)^2)$$

A.N. U = 100, 200 keV, $E_0 = m_e c^2 = 511$ keV

$$(v_e/c)^2 = 1 - 1 / (1 + 100 / 511)^2, v_e/c = 0.548 \sim 1 / 1.82 \sim 1 / 2$$

$$(v_e/c)^2 = 1 - 1 / (1 + 200 / 511)^2, v_e/c = 0.695 \sim 1 / 1.4$$

Facteur de Lorentz

1.1955

1.3908

Mesure EELS - Distance d'atténuation sur un TEM U = 100, 200 keV

$L = \gamma v_e / \omega = \gamma c \cdot T / (1.82 \cdot 2\pi) = \gamma / 2\pi \cdot \lambda_0 / 1.82$ où λ_0 désigne la longueur d'onde dans le vide du photon correspond à la perte d'énergie considérée

A.N. U = 100 keV Pour une perte de 1 eV, $\lambda_0 = 1240$ nm, $L = 1.1955 \times 1240 / (2\pi \cdot 1.82) = 130$ nm

Pour une perte de 2 eV, $\lambda_0 = 620$ nm, $L = 1.1955 \times 620 / (2\pi \cdot 1.82) = 65$ nm

U = 200 keV Pour une perte de 1 eV, $\lambda_0 = 1240$ nm, $L = 1.3908 \times 1240 / (2\pi \cdot 1.44) = 191$ nm

Pour une perte de 2 eV, $\lambda_0 = 620$ nm, $L = 1.3908 \times 620 / (2\pi \cdot 1.44) = 95$ nm

HAADF (Wikipedia) High-angle annular dark-field imaging (HAADF) is an STEM technique which produces an annular dark field image formed by very high angle, incoherently scattered electrons (Rutherford scattered from the nucleus of the atoms) — as opposed to Bragg scattered electrons. This technique is highly sensitive to variations in the atomic number of atoms in the sample (Z-contrast images).[3]